

Atmospheric Pressure Plasma Technology For Ultra-Precision Engineering Of Optics For Applications In Aerospace, Defence And Science

Adam Bennett

Adam Bennett

- Military Officer
- First Degree Physics
- Post Graduate Masters Nanotechnology: First Class Equivalent – Highest Grade On The Programme
- Post Graduate Certificate Ultra Precision Engineering
- PhD in Ultra Precision Engineering: Plasma (submission April 2018)

Aim

Applications

Background

Plasma Figuring Machines

Microwave Induced Plasma Systems

Characterisation Method Developed

Plasma Processing of Optics

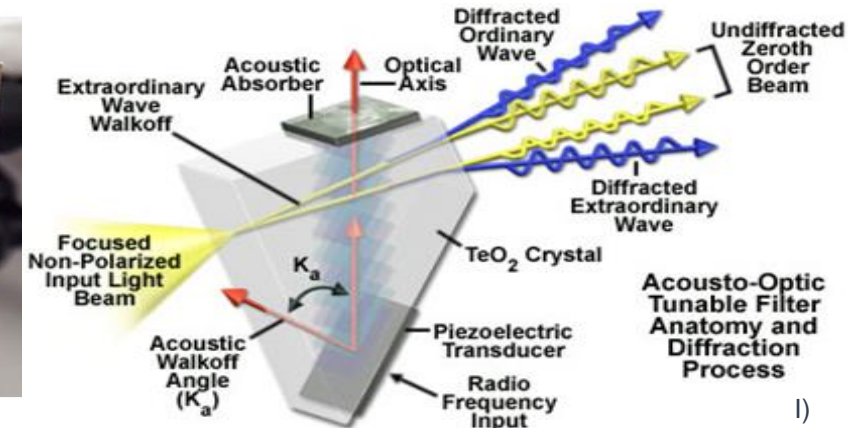
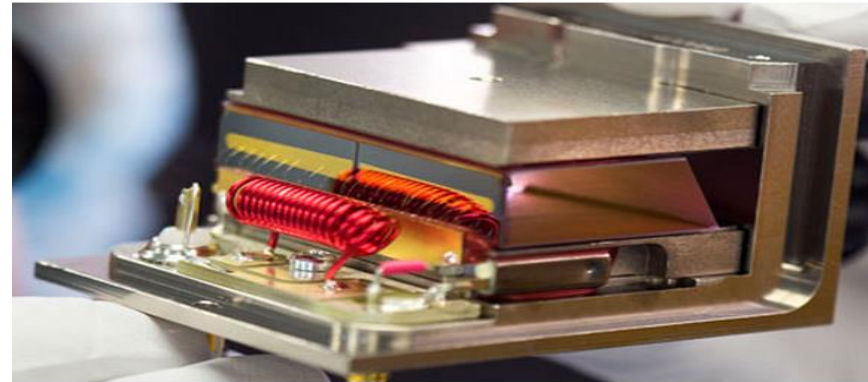
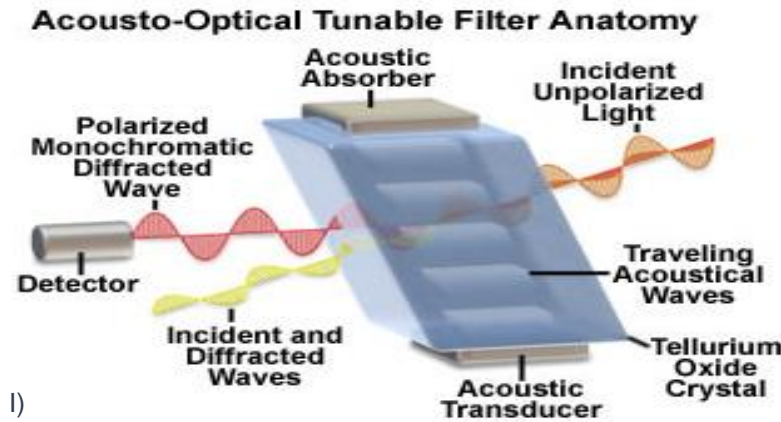
Aim

Microwave Plasma Energy Beam
 100mm by 100mm Optics
 Crystal Quartz

Material Removal Rate of 0.1mm³/min
 Form accuracy < 10nm RMS
 Surface texture < 1nm RMS

Applications

Acousto-Optics: Beam Deflectors, Frequency Shifters, Modulators, Q Switches

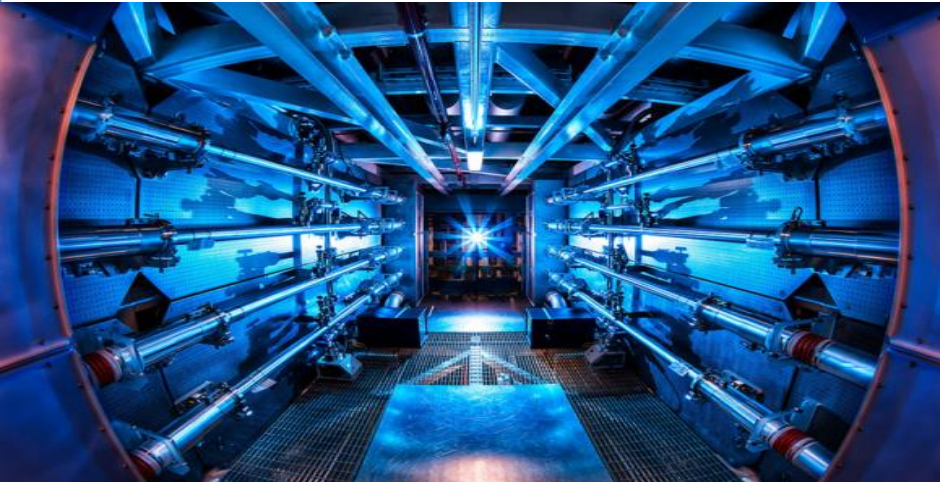


I) T. Fellers, M. Davidson, 2009, Acousto-Optic Tunable Filters, Report for the National High Magnetic Field Laboratory, USA

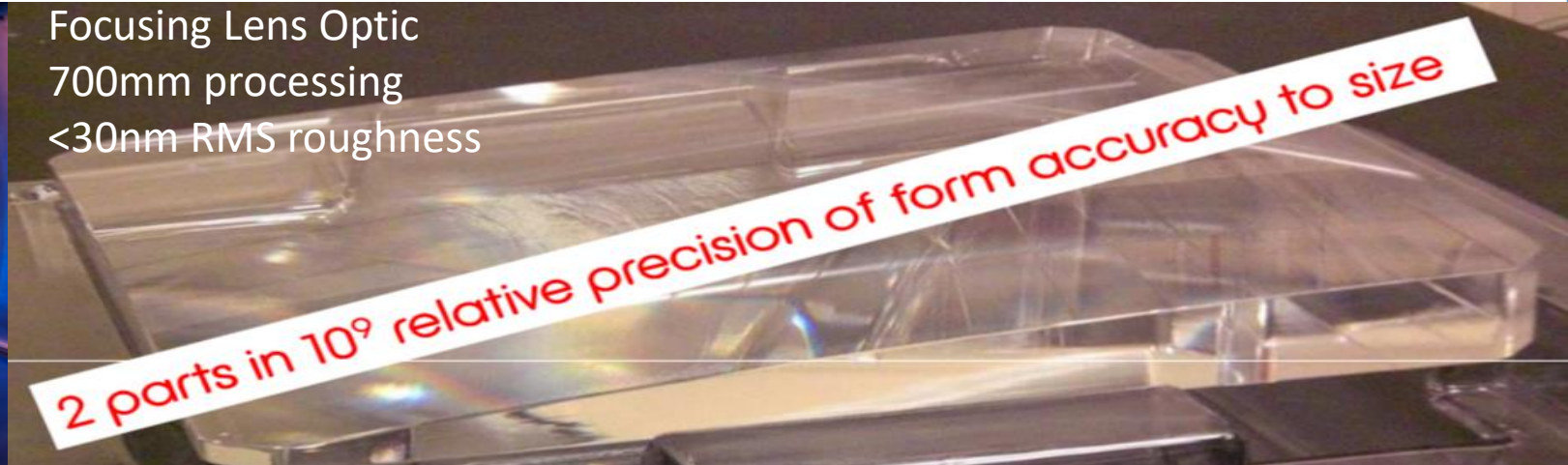
II) Acousto-Optic, <http://goochandhousego.com/capabilities/acousto-optic-capabilities>, 21/04/2015

Other Applications

Fusion Energy Research: Using Metre Scale Optics to Focus High Power Laser Beams



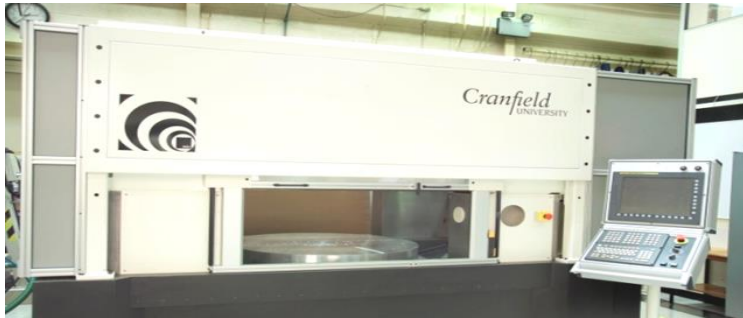
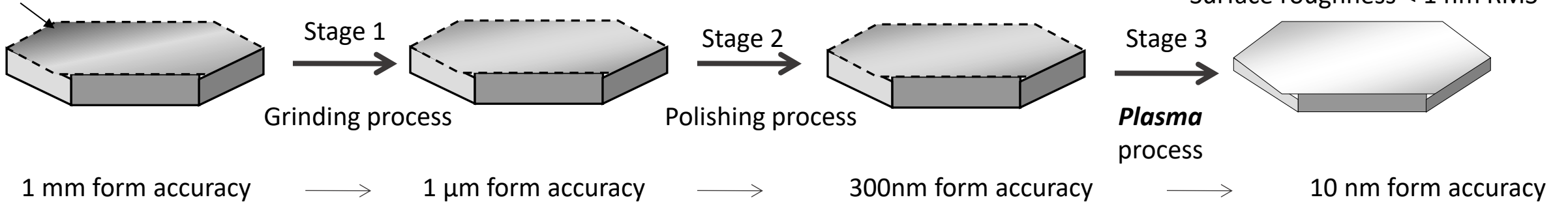
Focusing Lens Optic
700mm processing
<30nm RMS roughness



III) Cold Fusion, <http://phys.org/news/2013-08-laser-fusion-yields-energy.html>, 21/04/2015

Ultra Precision Surface Processing Route for Large Optics

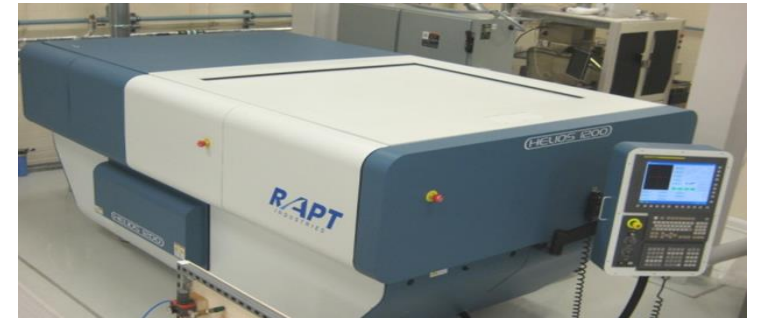
Metre scale
 optical component



*BoX
 (Ultra precision grinding)*



*Polishing machine
 (Robot)*

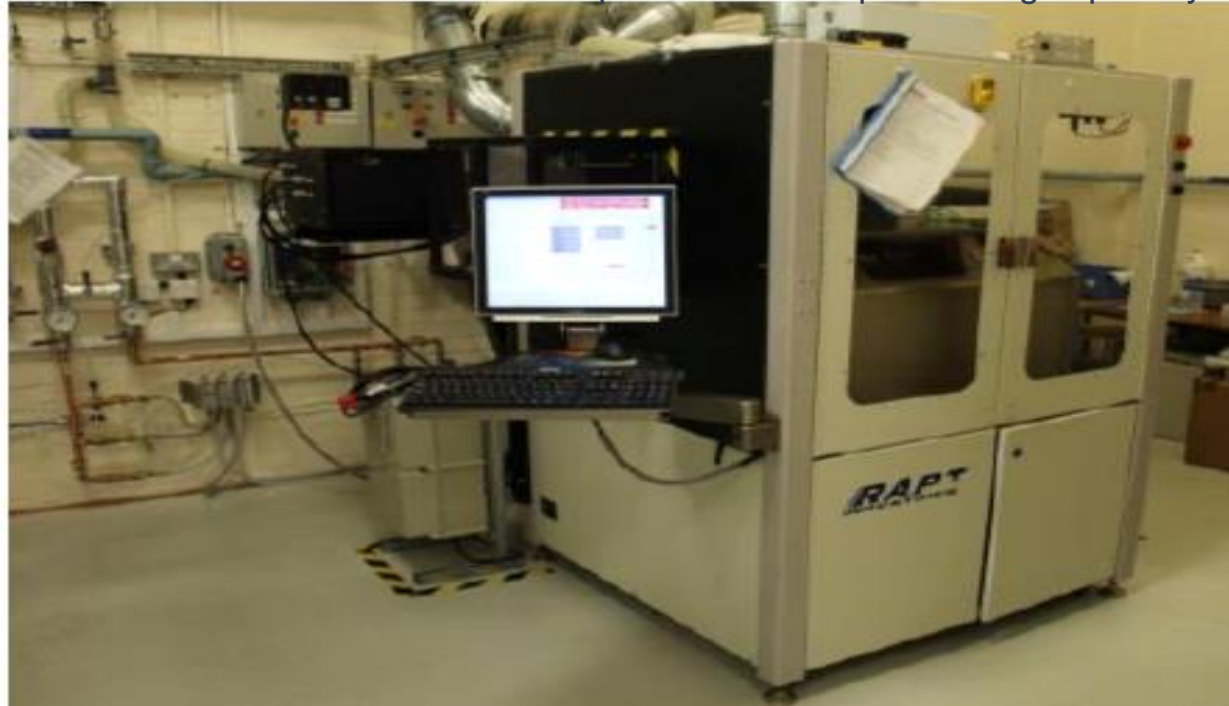


*Helios1200
 (Plasma figuring machine)*

Plasma Figuring Machines at Cranfield University

RAP Plasma Figuring Machine

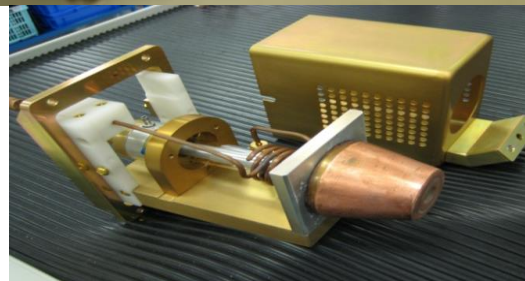
300mm x 300mm optical substrate processing capability



Atmospheric Pressure
Plasma Figuring

Helios Plasma Figuring Machine

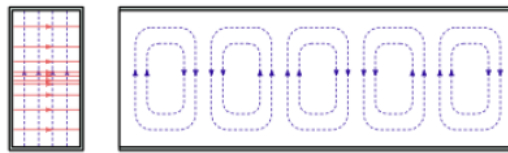
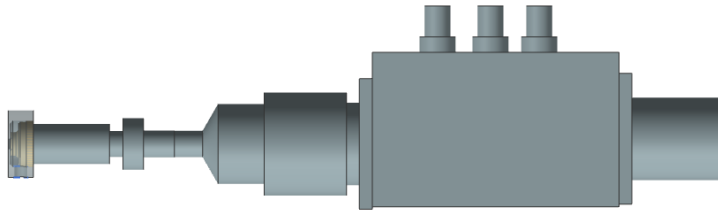
1200mm x 1200mm optical substrate processing capability



Both plasma figuring machines currently employ an Inductively Coupled Plasma torch

Microwave Induced Plasma Systems

Coaxial Electrode System



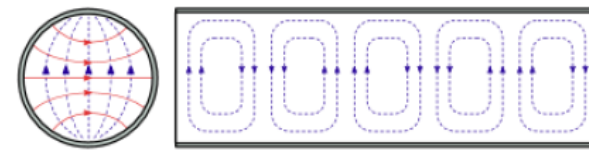
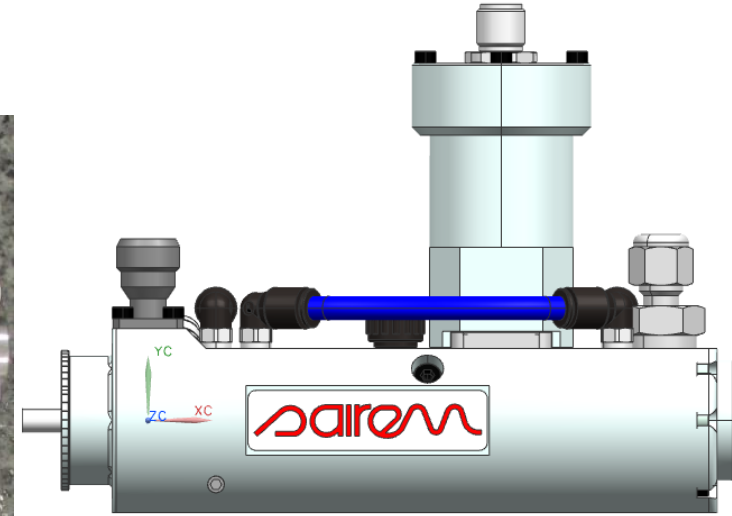
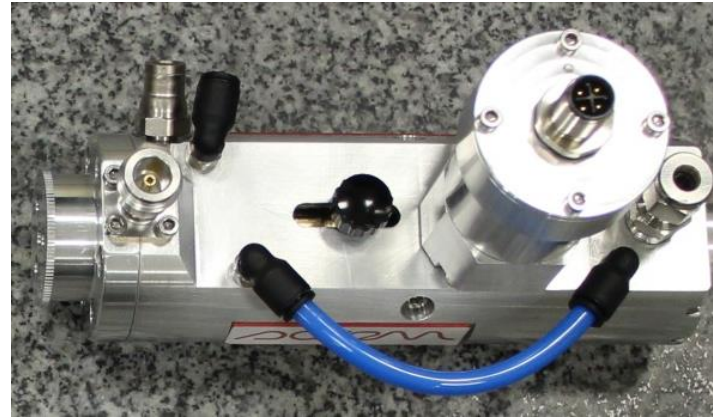
TE₁₀

— E field
— H field

TE f = TM f

$$f_{mni} = \frac{c}{2\sqrt{\mu_r \epsilon_r}} \cdot \sqrt{\left(\frac{m}{a}\right)^2 + \left(\frac{n}{b}\right)^2 + \left(\frac{l}{d}\right)^2}$$

Surface Wave Launcher System



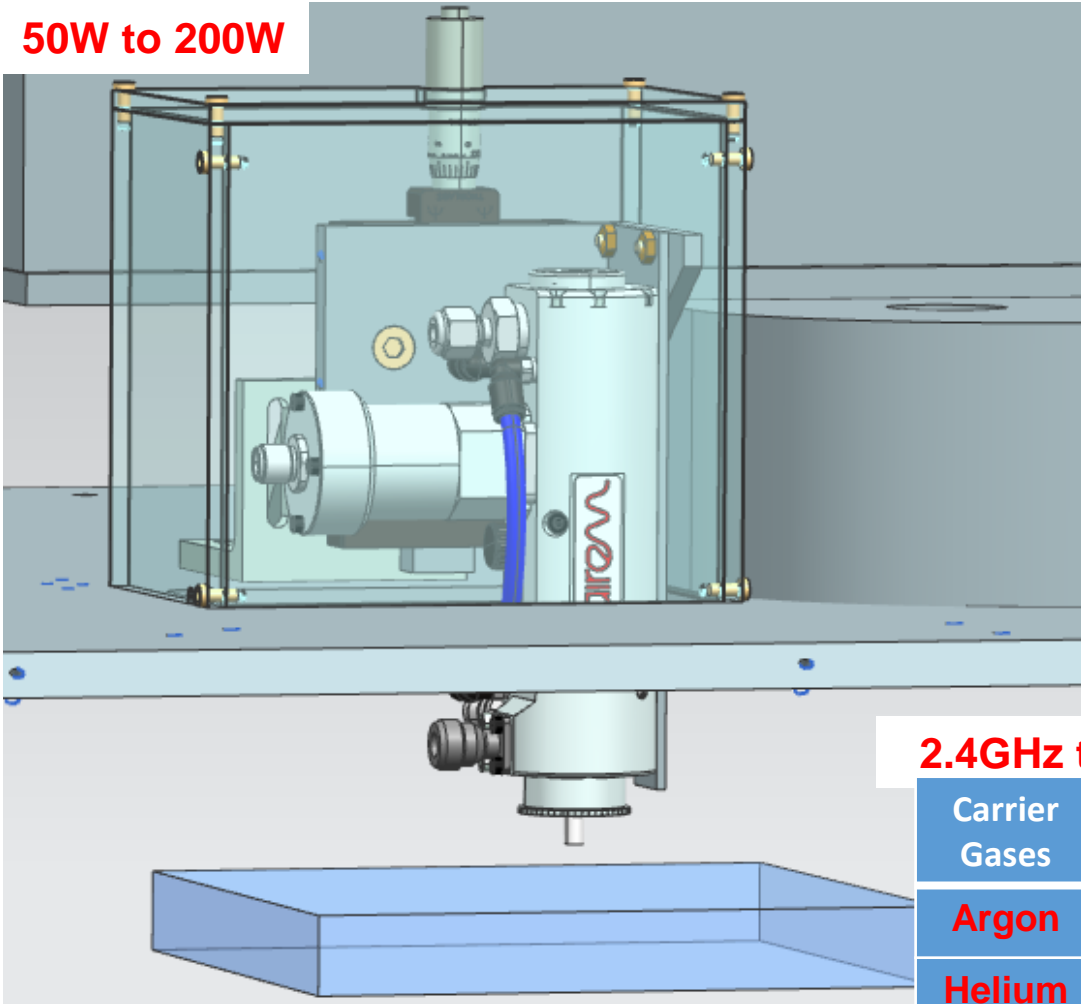
TE₁₁

$$f_{mnp} = \frac{c}{2\pi\sqrt{\mu_r \epsilon_r}} \cdot \sqrt{\left(\frac{X'_{mn}}{R}\right)^2 + \left(\frac{p\pi}{L}\right)^2}$$

TE f ≠ TM f

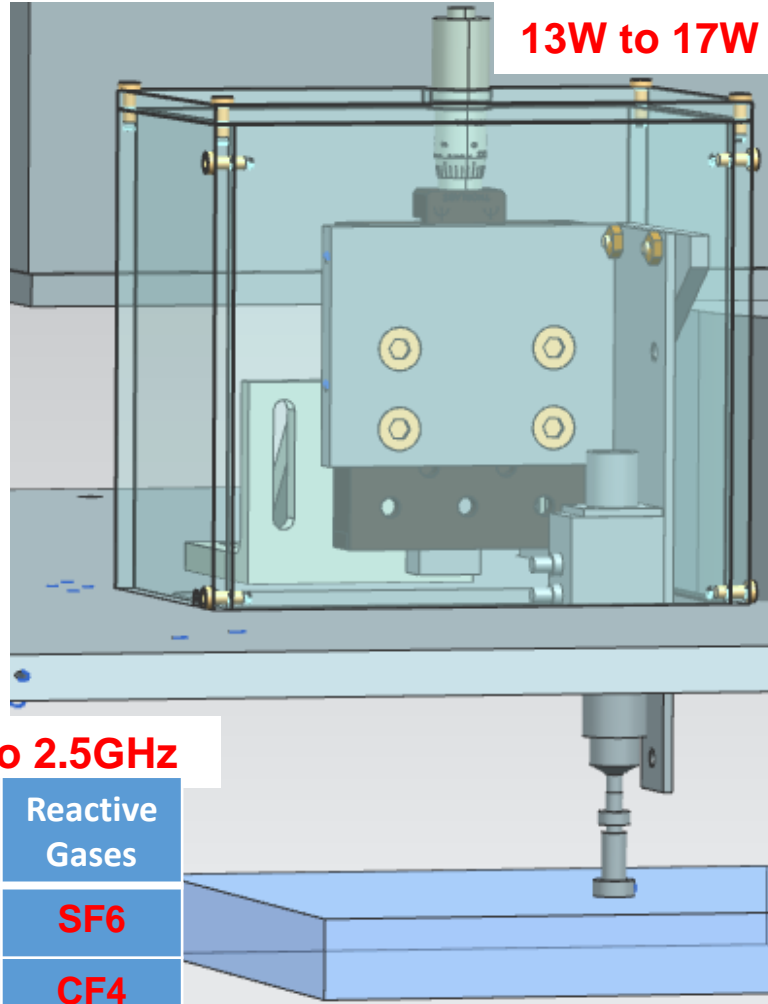
Surface Wave Launcher System

50W to 200W



Coaxial Electrode System

13W to 17W



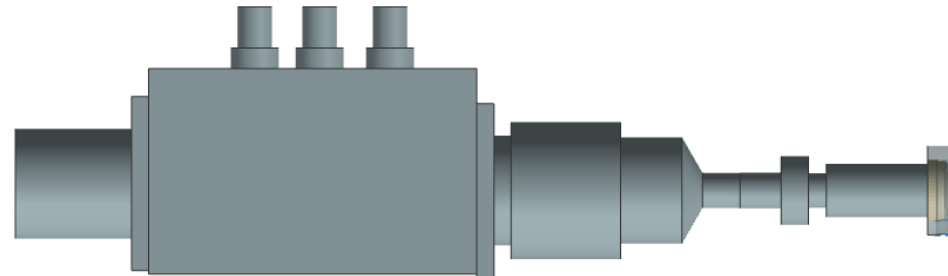
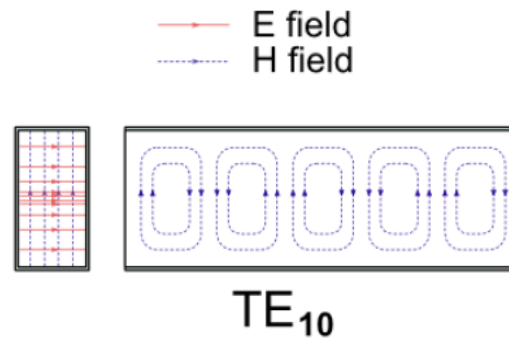
2.4GHz to 2.5GHz

Carrier Gases	Reactive Gases
Argon	SF6
Helium	CF4

Coaxial Electrode Microwave Induced Plasma Torch

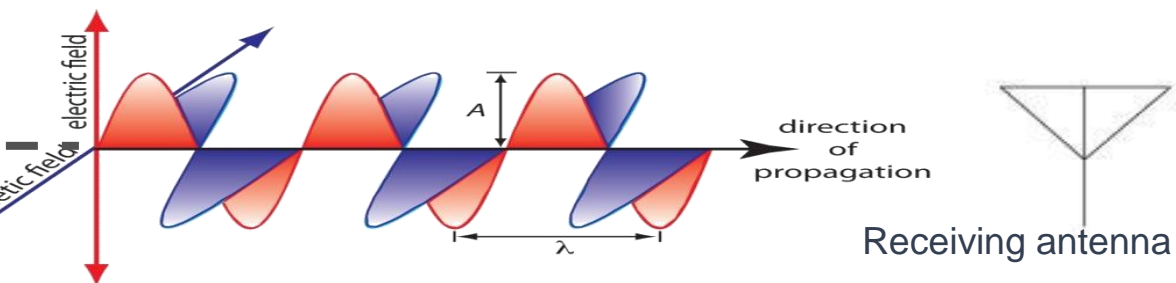
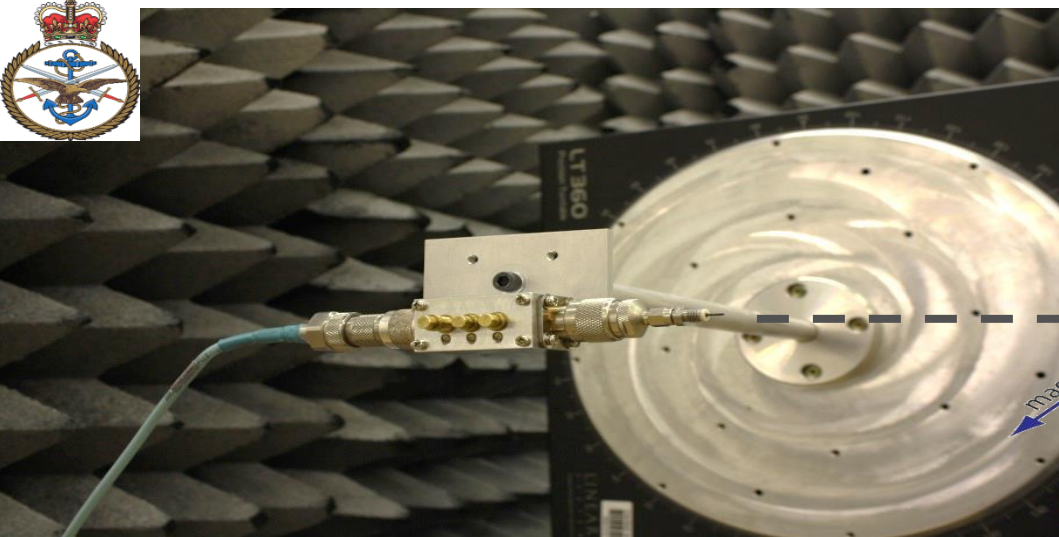
Transverse Electric frequency = Transverse Magnetic frequency

$$f_{mni} = \frac{c}{2\sqrt{\mu_r \epsilon_r}} \cdot \sqrt{\left(\frac{m}{a}\right)^2 + \left(\frac{n}{b}\right)^2 + \left(\frac{l}{d}\right)^2}$$

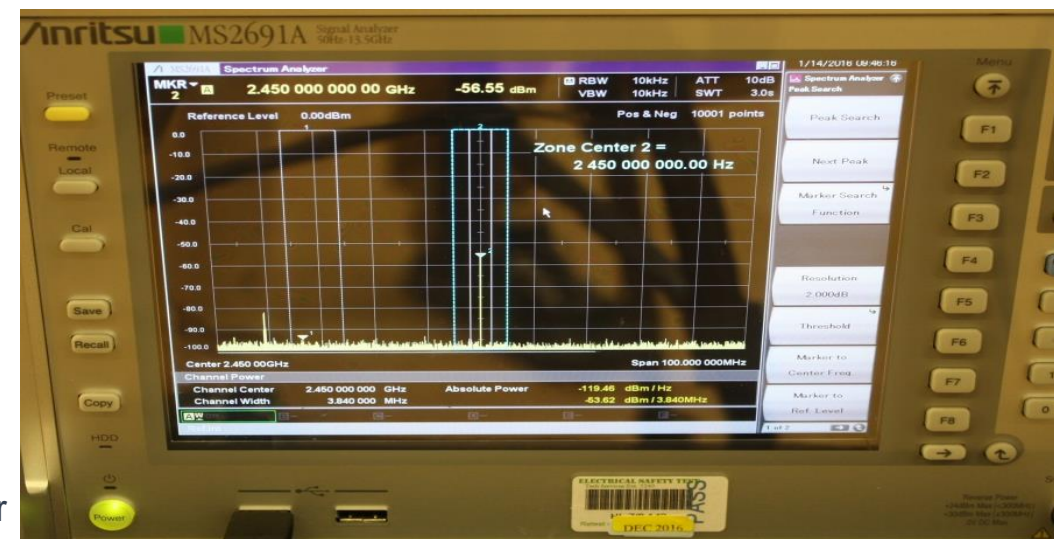


Coaxial Electrode Microwave Induced Plasma Torch

Military Microwave Anechoic Chamber



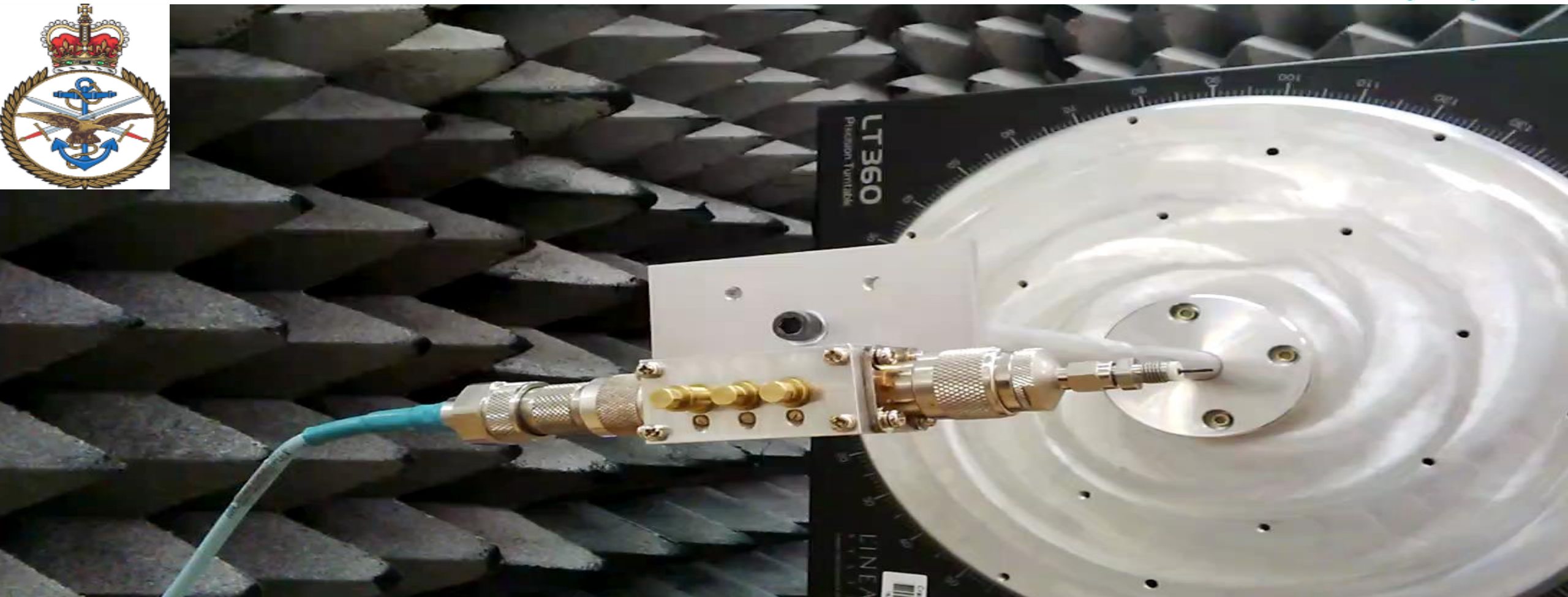
Adtec torch placed into RADAR/MWDAR Anechoic Chamber



Anritsu MS461221 spectrum analyser

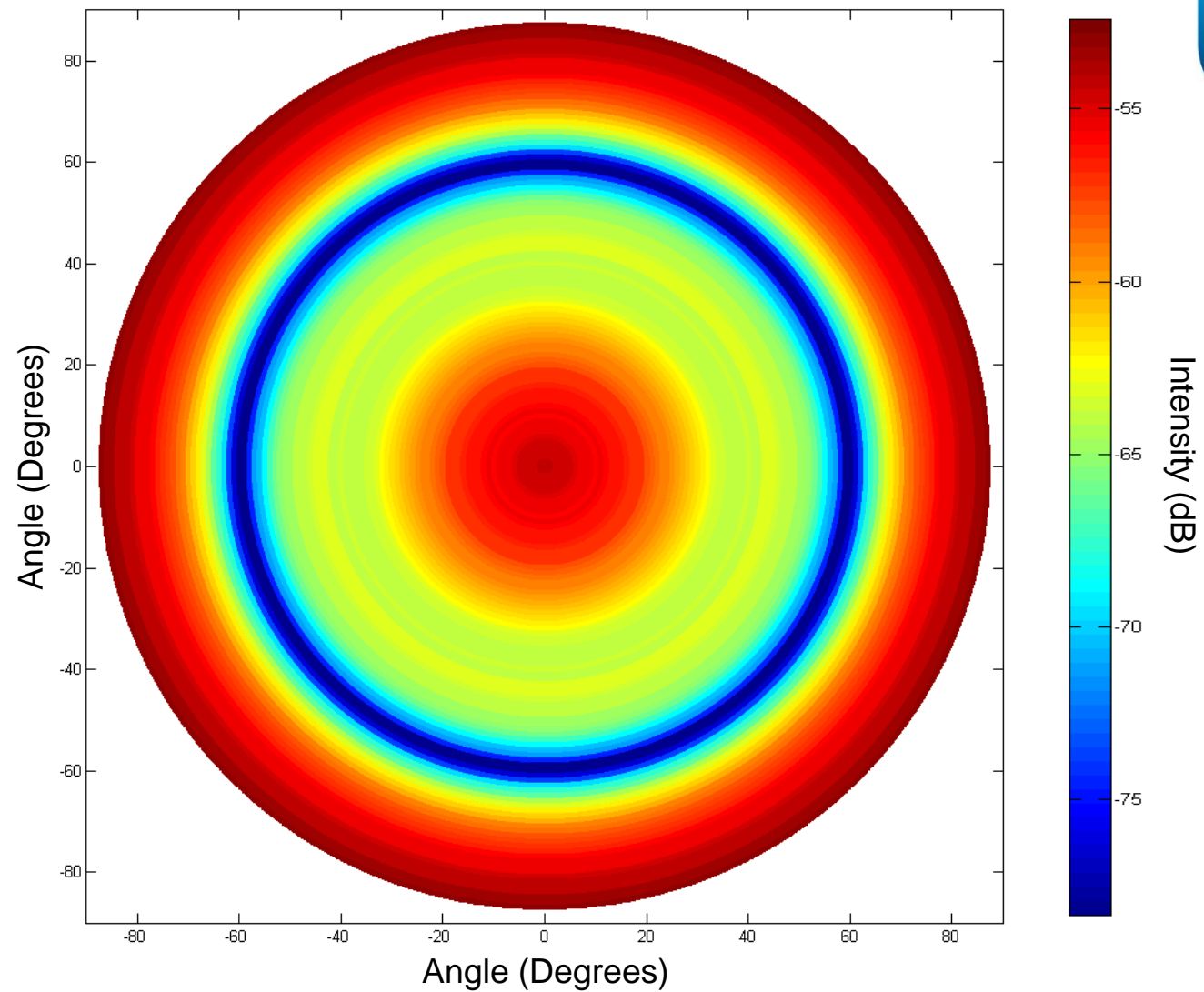
Coaxial Electrode Microwave Induced Plasma Torch

Military Microwave Anechoic Chamber

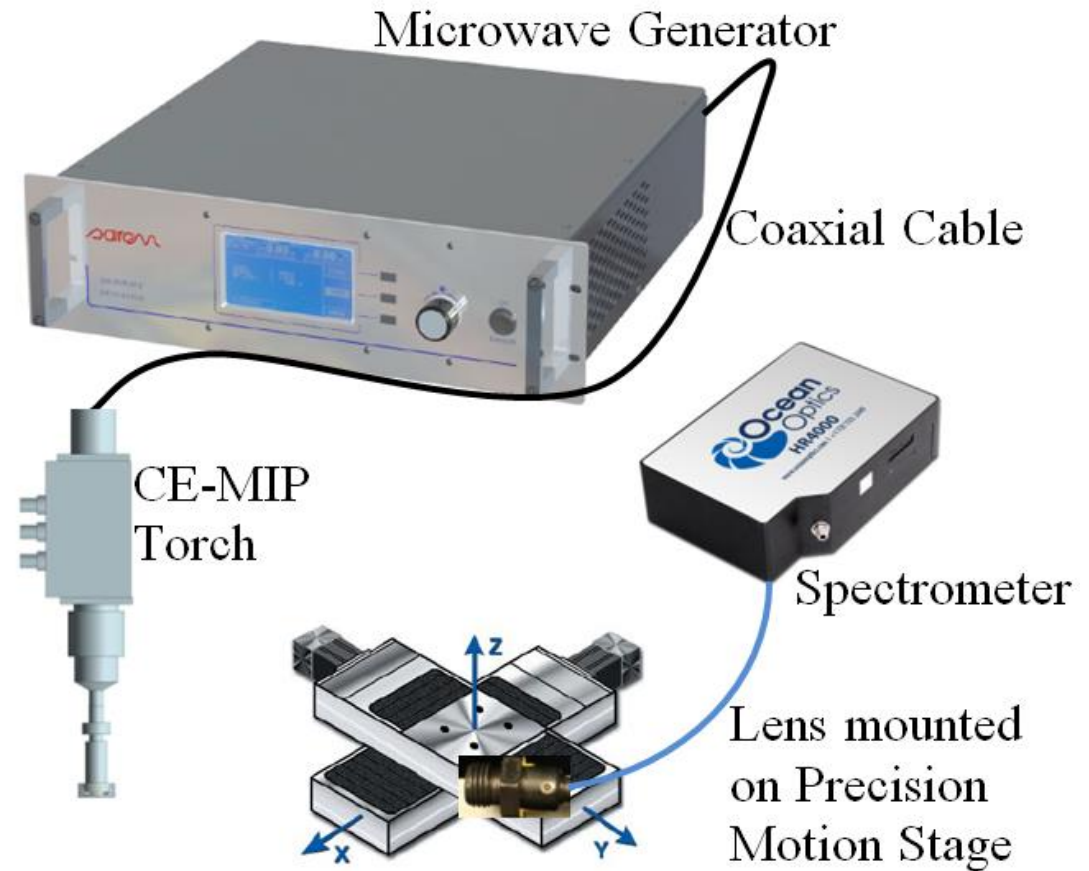
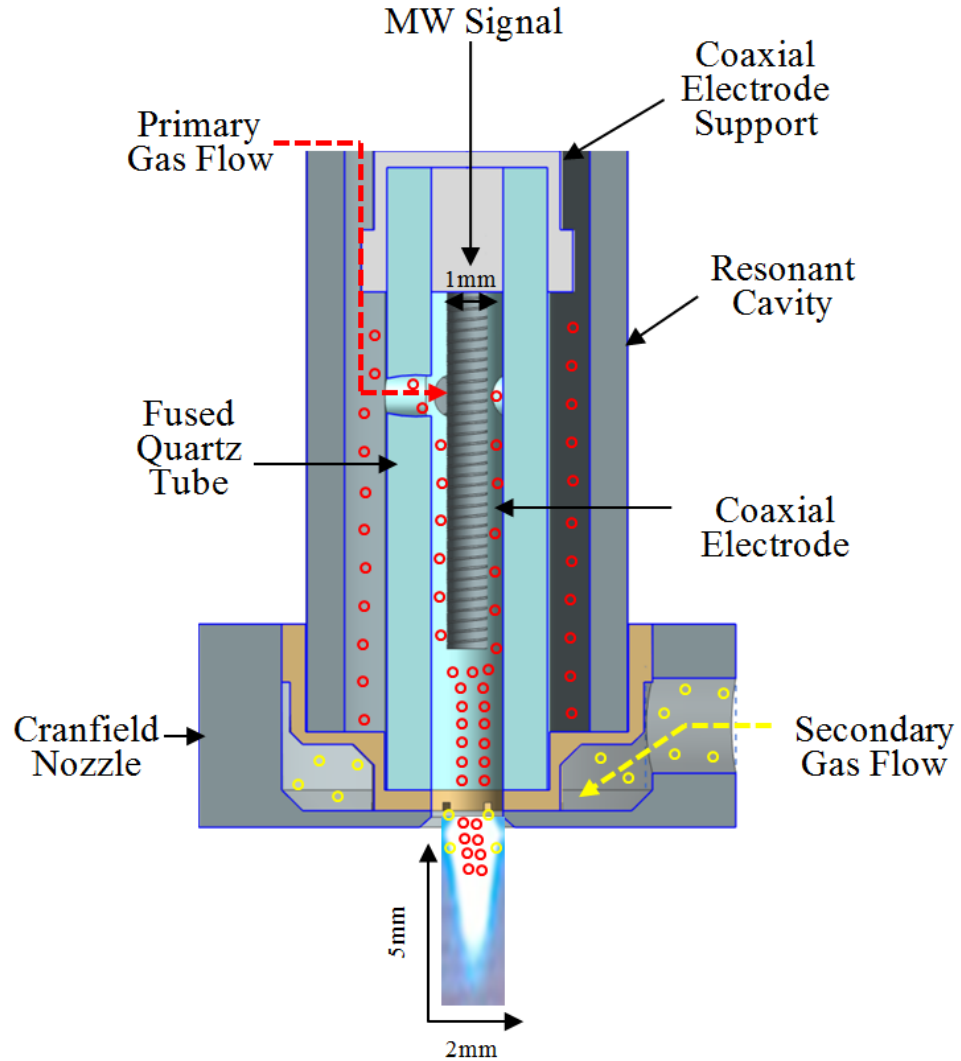


Coaxial Electrode Microwave Induced Plasma Torch

Directionality of the Microwave Energy being Emitted from the Adtec Electrode

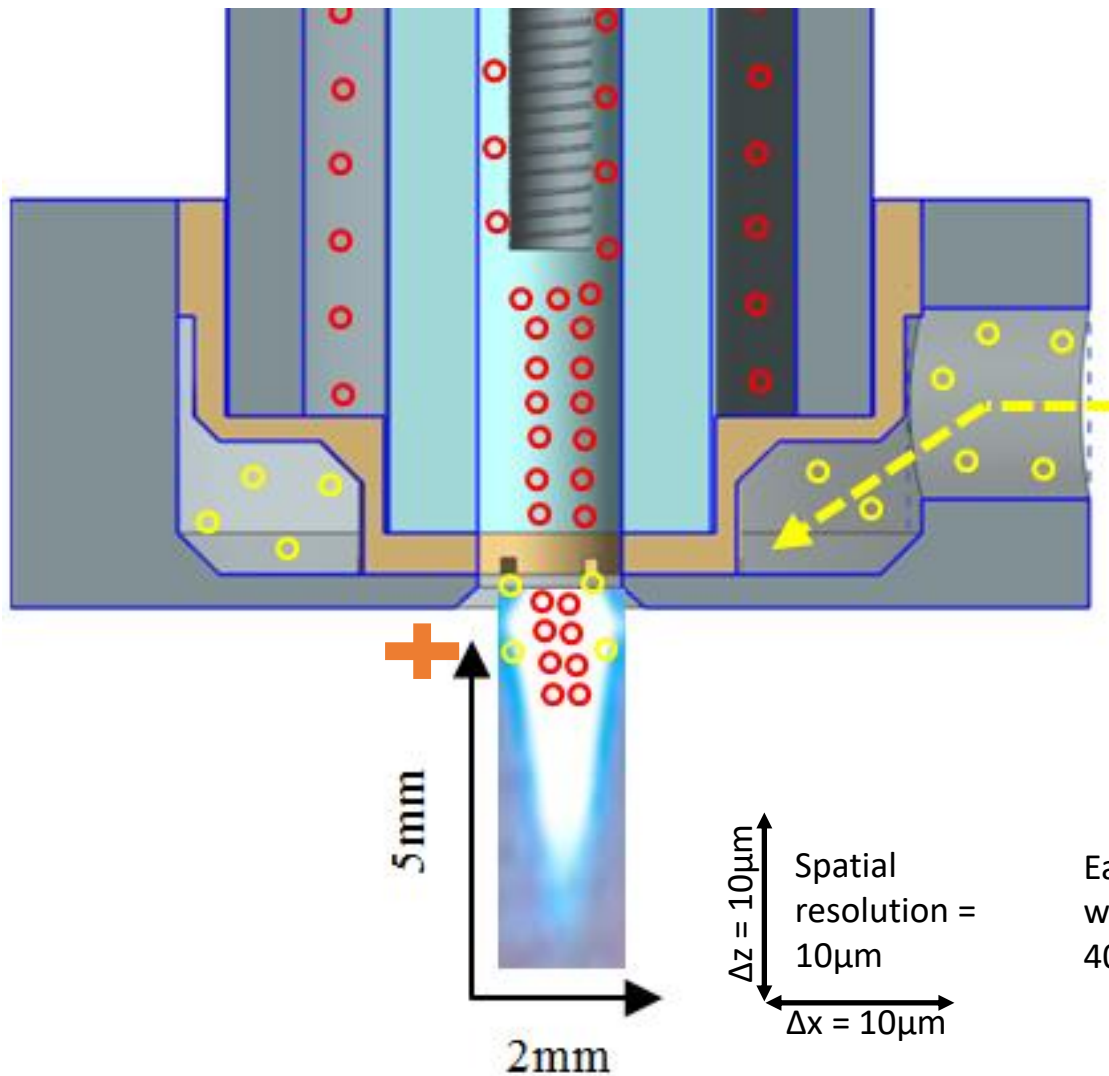


Coaxial Electrode Microwave Induced Plasma Torch Characterisation by Optical Emission Spectroscopy Experimental Setup

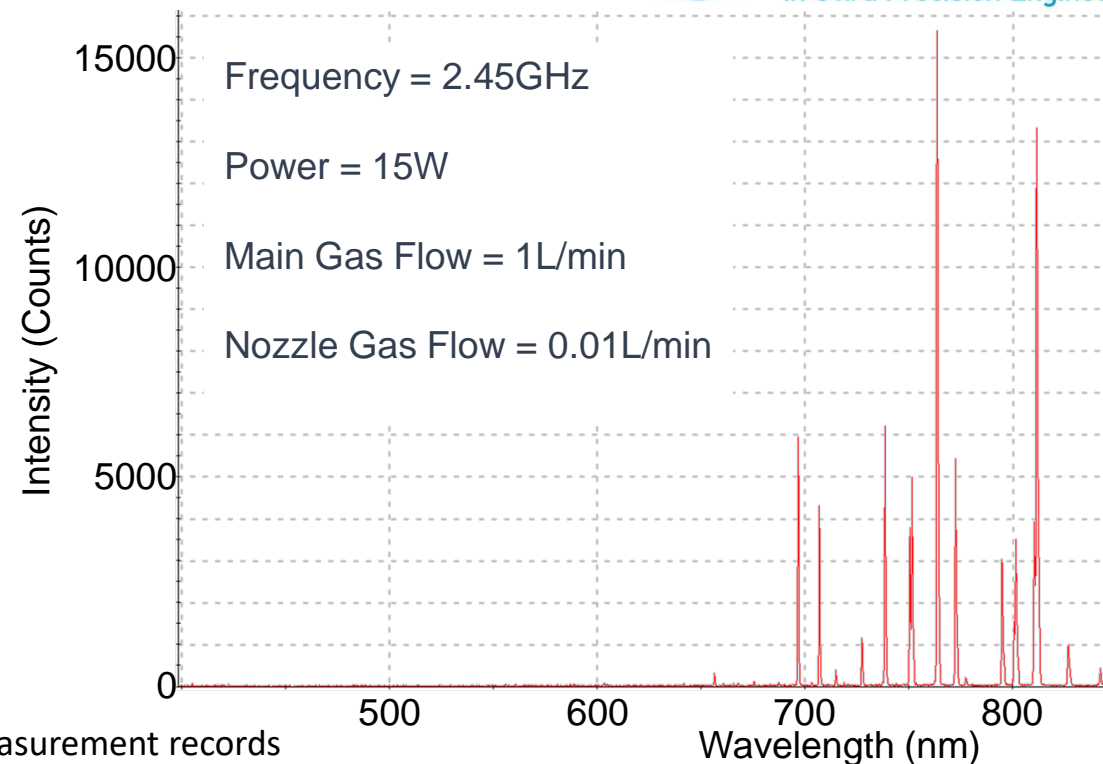


Coaxial Electrode Microwave Induced Plasma Torch

Optical Emission Spectroscopy



Each measurement records wavelengths from 400nm to 850nm



Lens Connected To Spectrometer

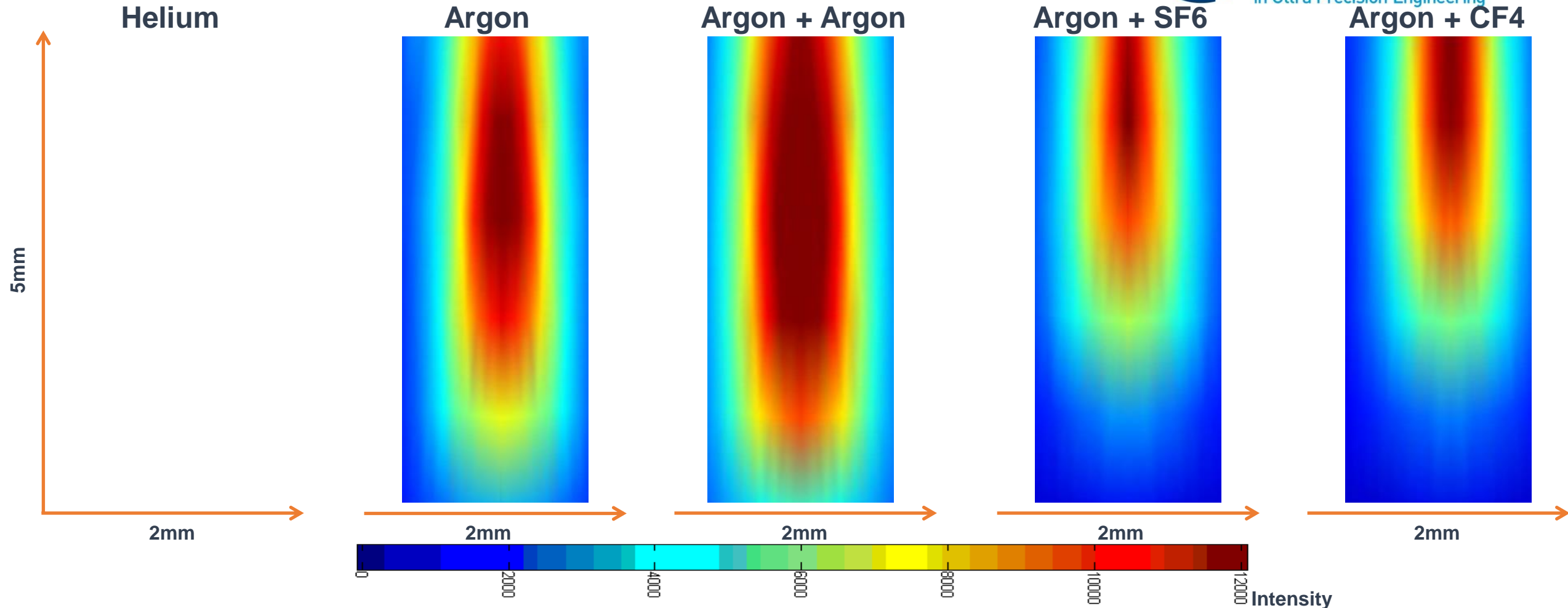


Coaxial Electrode Microwave Induced Plasma Torch

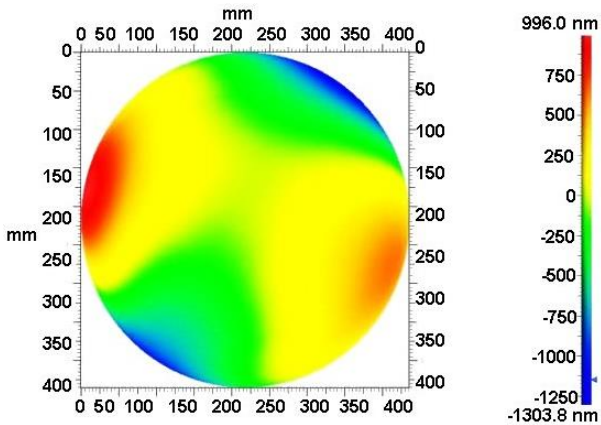
Optical Emission Spectroscopy Results

Power = 15W; Frequency = 2.45GHz;

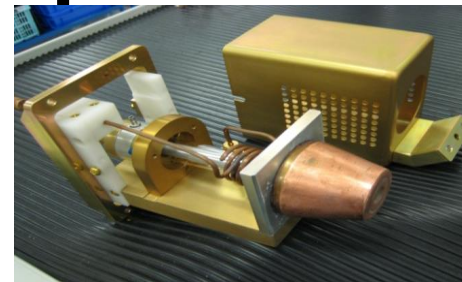
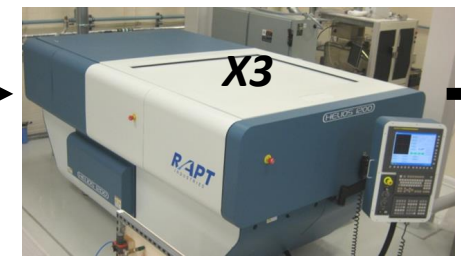
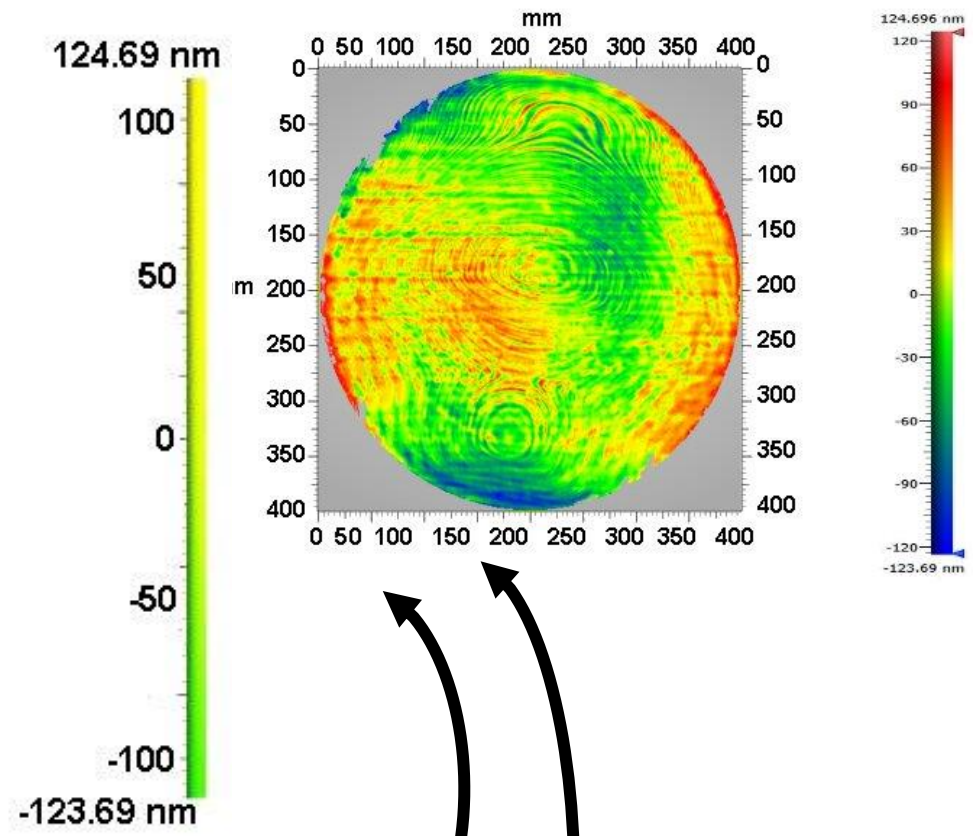
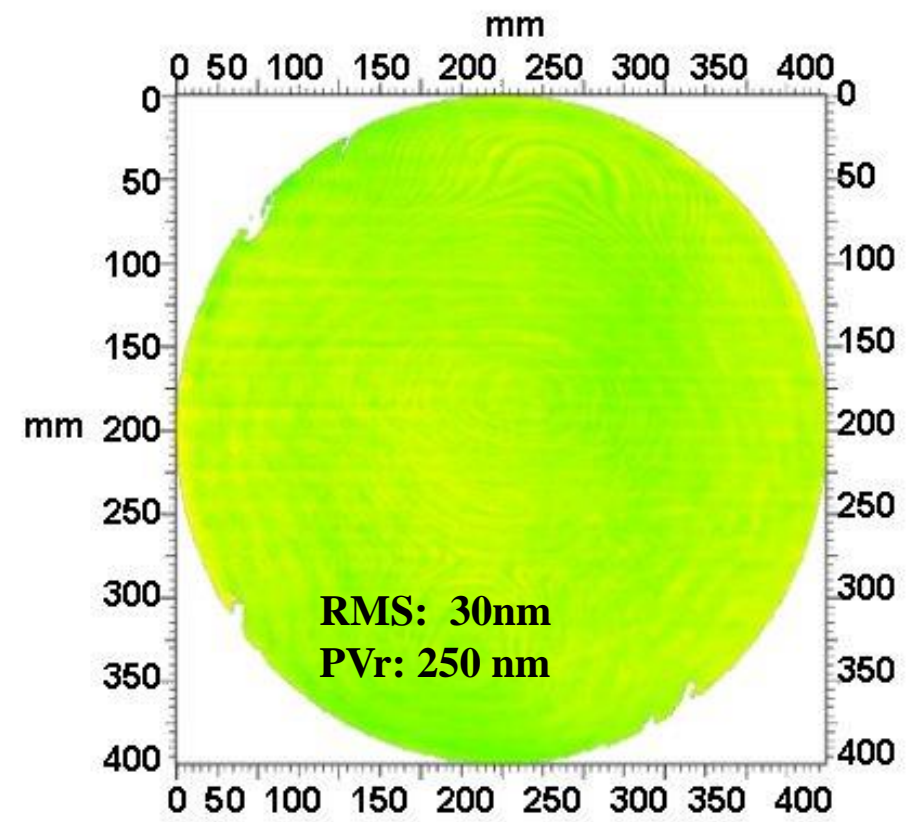
Main Gas Flow = 1L/min; Nozzle Gas Flow = 0.01L/min



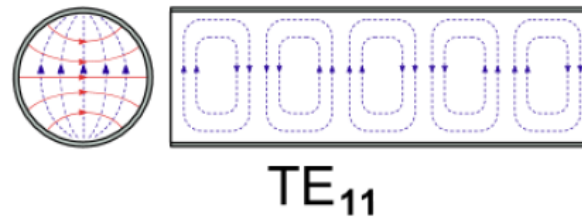
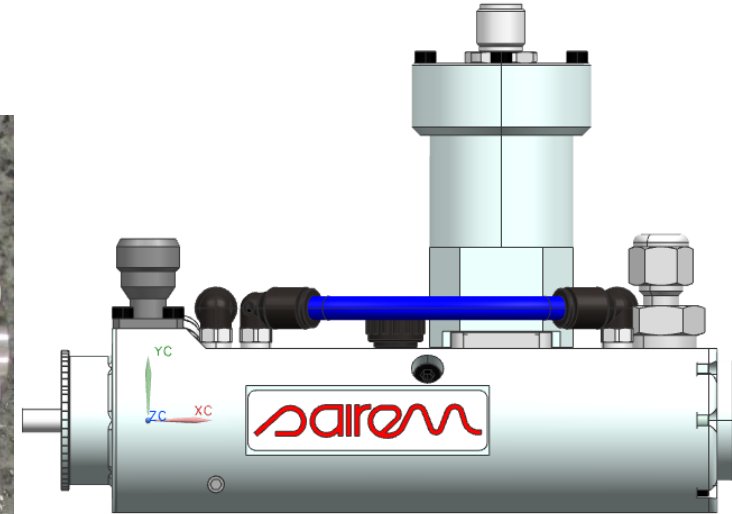
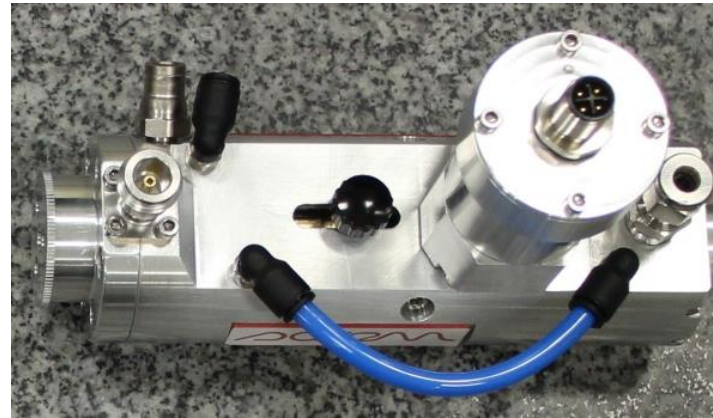
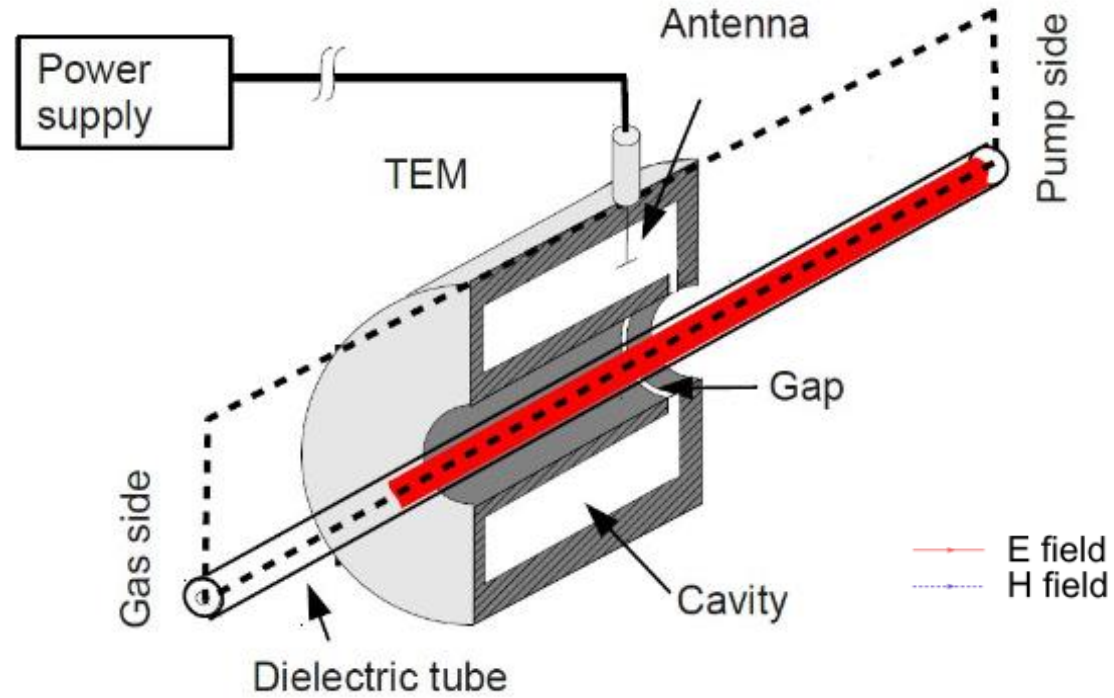
Previous Plasma Processing Results



Initial figure error



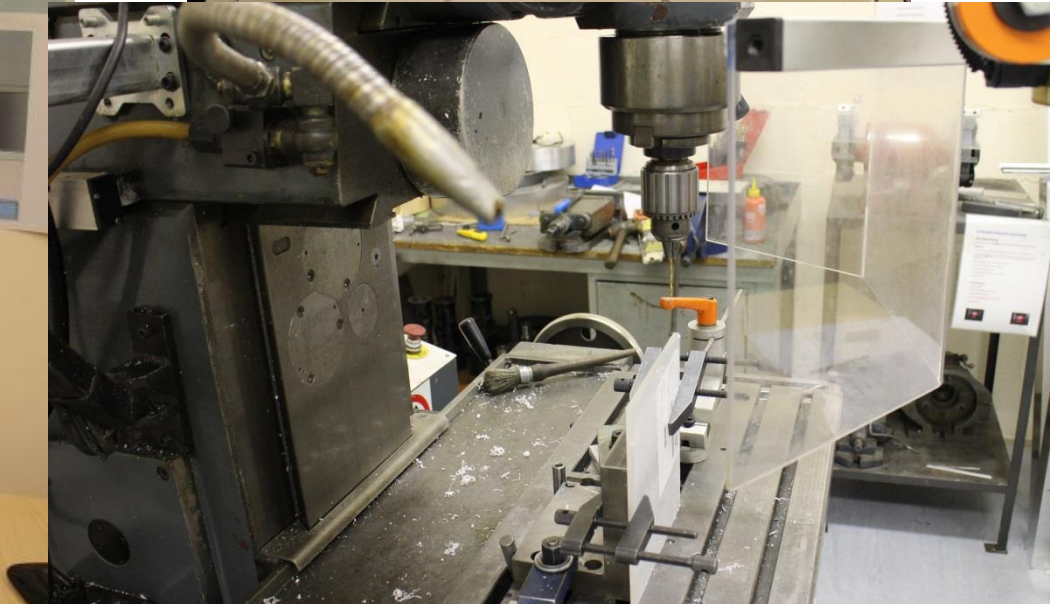
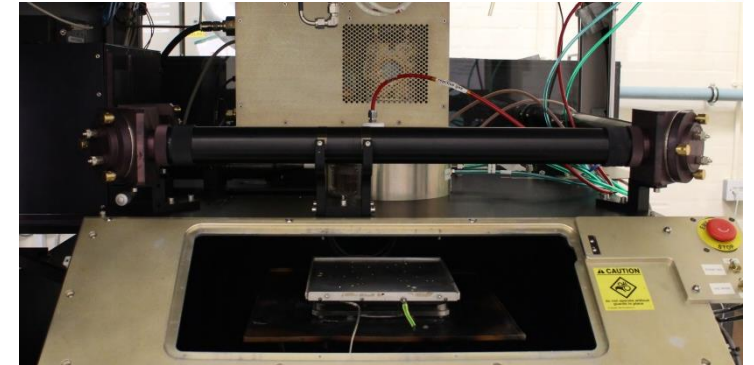
Surface Wave Launched Microwave Induced Plasma Torch



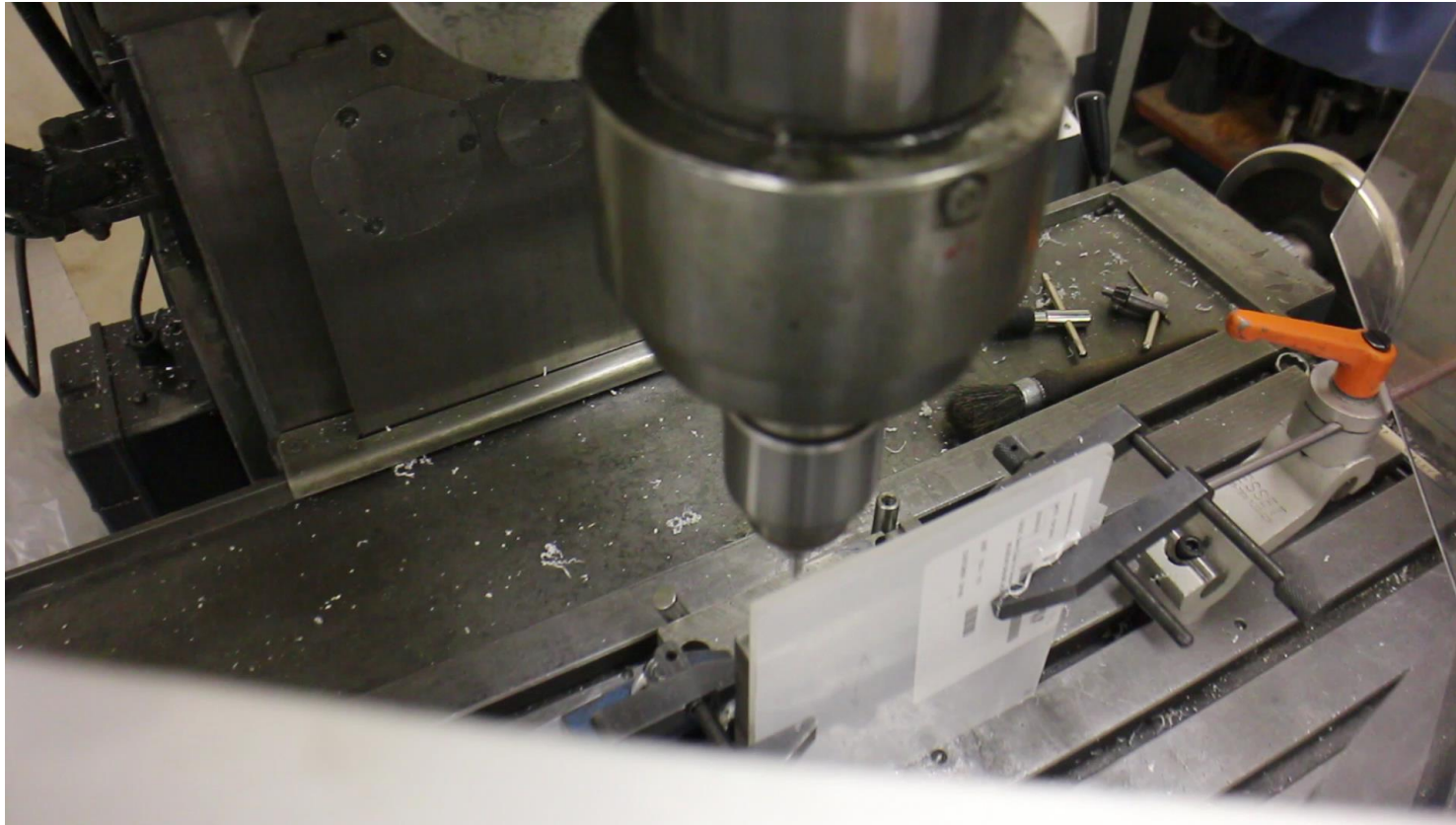
TE f ≠ TM f

$$f_{mnp} = \frac{c}{2\pi\sqrt{\mu_r\epsilon_r}} \cdot \sqrt{\left(\frac{X'_{mn}}{R}\right)^2 + \left(\frac{p\pi}{L}\right)^2}$$

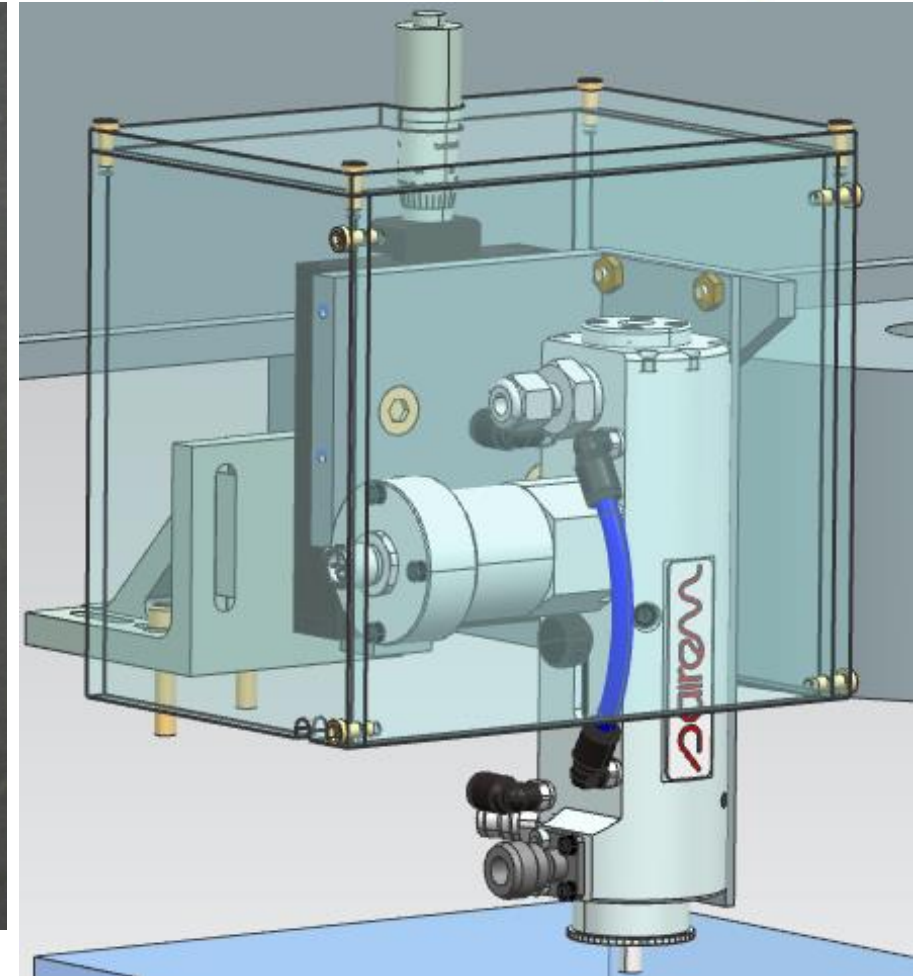
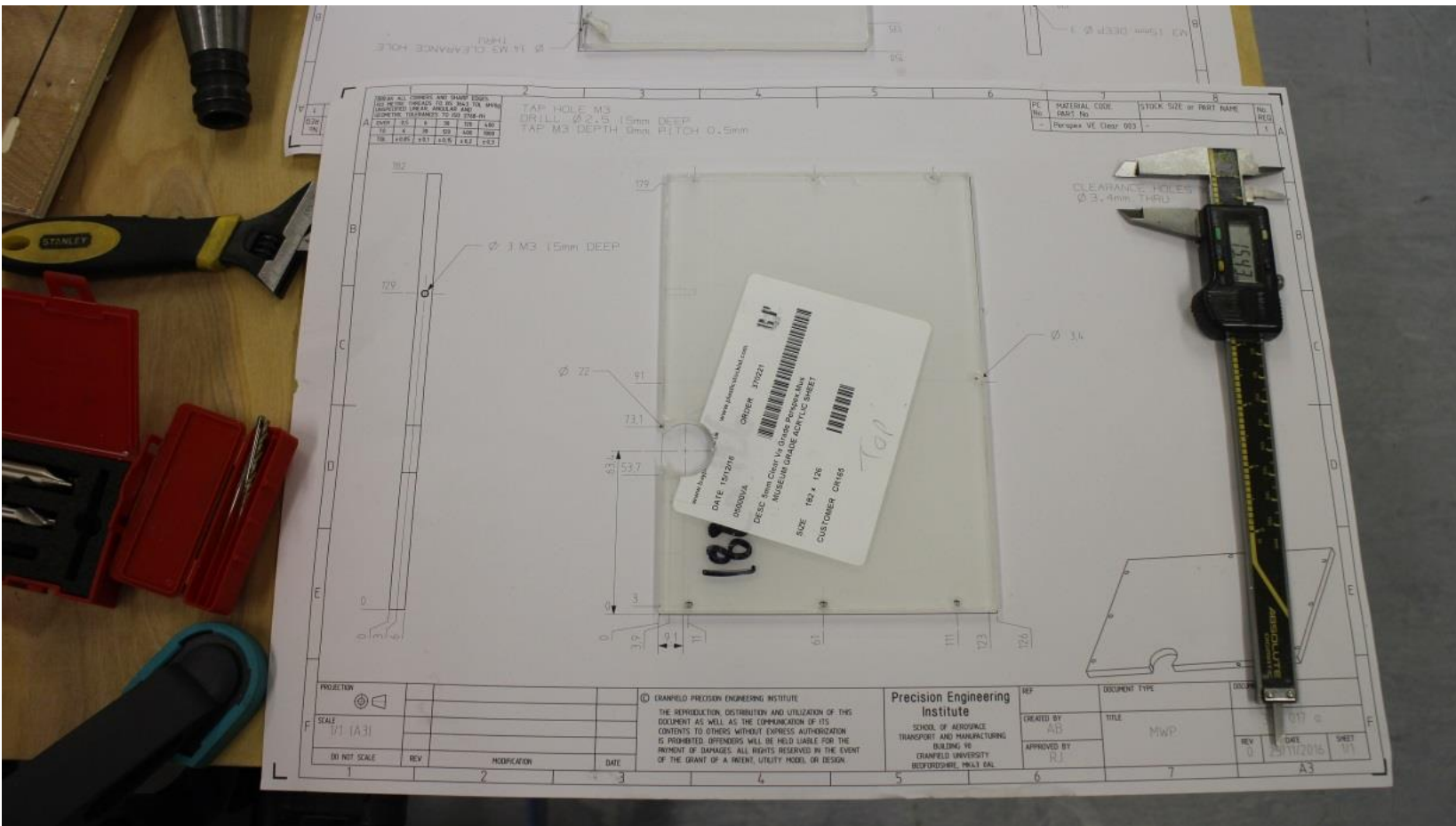
Microwave Plasma System & Enclosure Installation



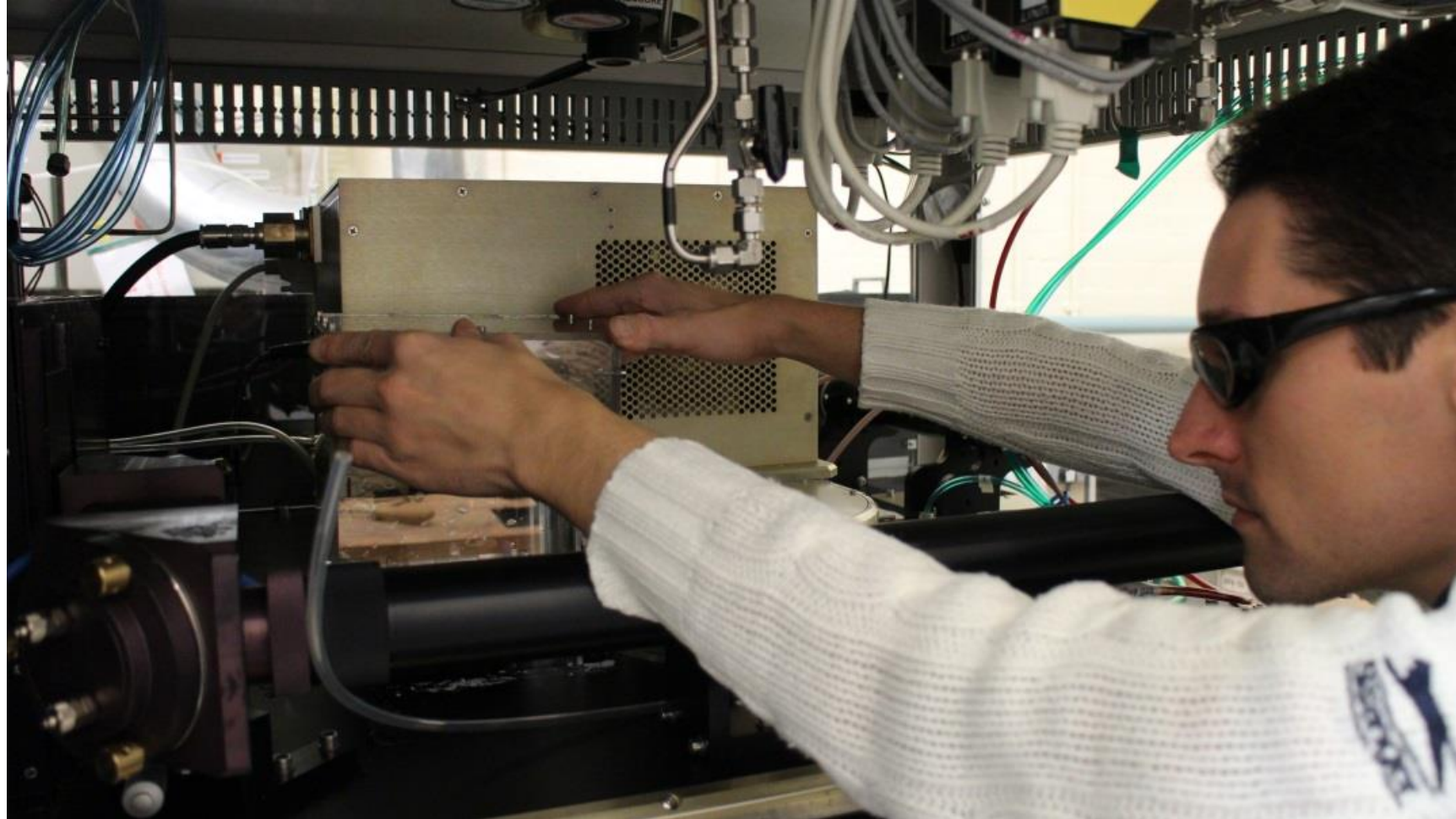
Microwave Plasma System & Enclosure Installation



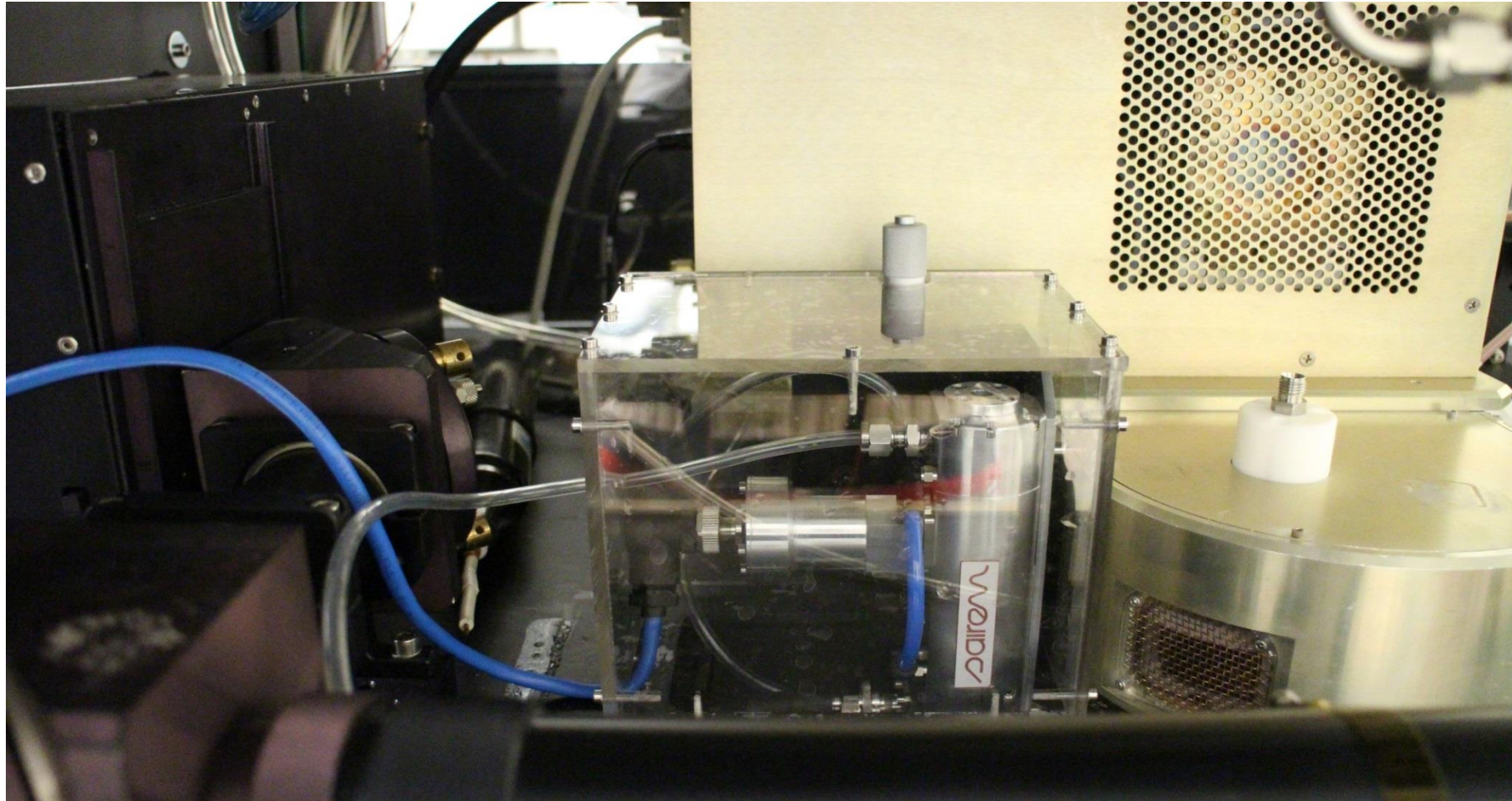
Microwave Plasma System & Enclosure Installation



Microwave Plasma System & Enclosure Installation



Microwave Plasma System & Enclosure Installation

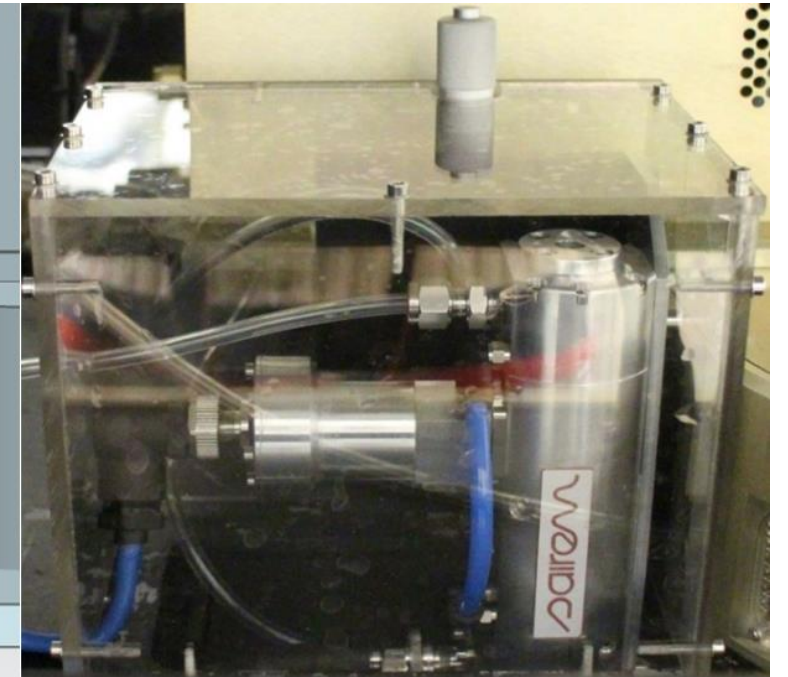
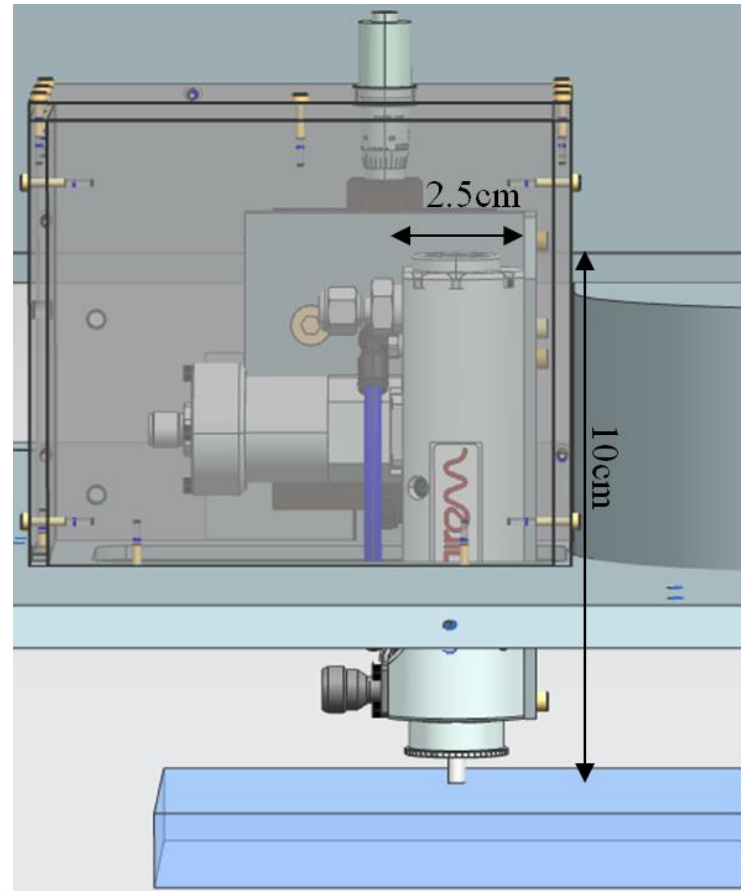


Plasma Processing

The Surface Wave Launcher Microwave Induced Plasma torch was placed into a bespoke enclosure within a Plasma Figuring machine.

Contains all UV(UV-A, UV-B, UV-C); radio-waves; micro-waves; and reactive atoms.

Enables rapid processing at atmospheric pressure.



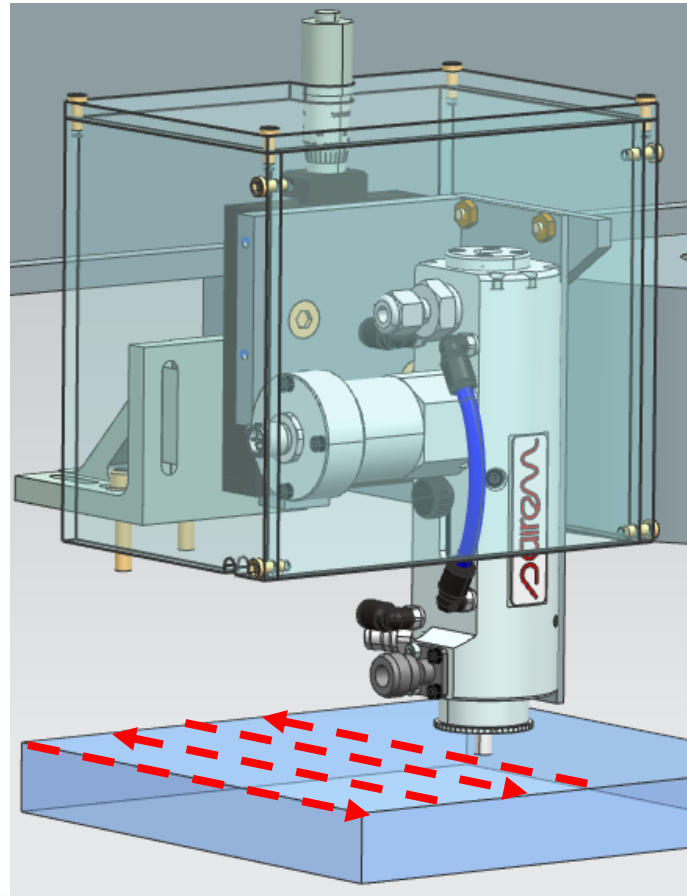
Plasma Processing

The Surface Wave Launcher Microwave Induced Plasma torch was placed into a bespoke enclosure within a Plasma Figuring machine.

Contains all UV(UV-A, UV-B, UV-C); radio-waves; micro-waves; and reactive atoms.

Enables rapid processing at atmospheric pressure.

Tool path: the route the torch moves with respect to the optic

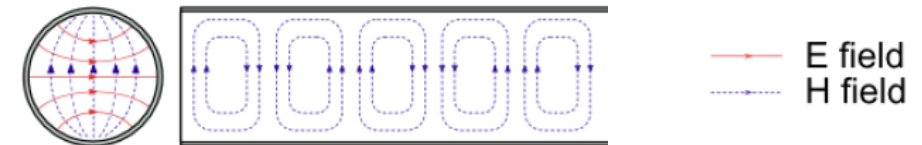


Frequency = 2.4GHz to 2.5GHz

Power = 100W to 200W

Main Gas Flow = 4L/min to 10L/min

Main Gas : Reactive Gas = 99.5% : 0.5% to 96% : 4%

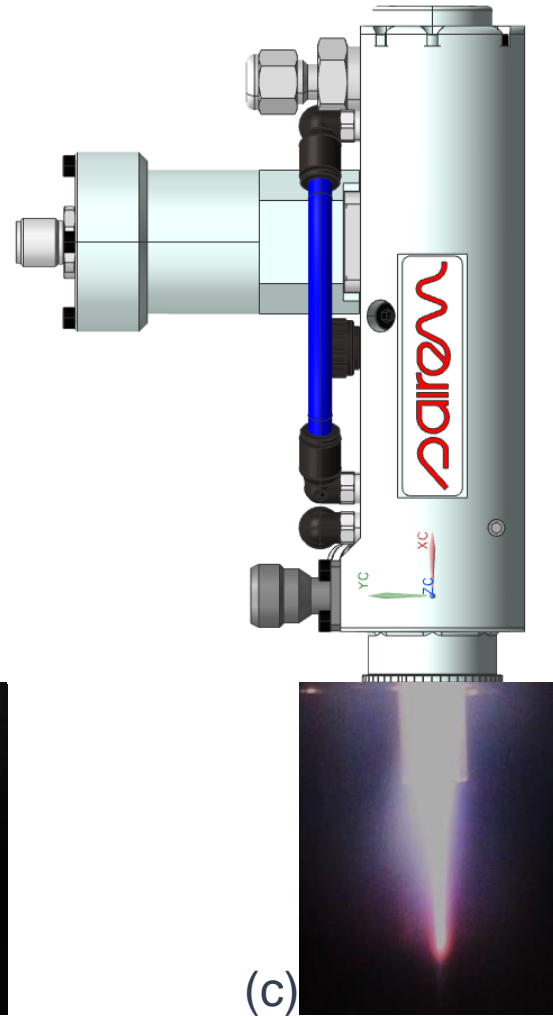
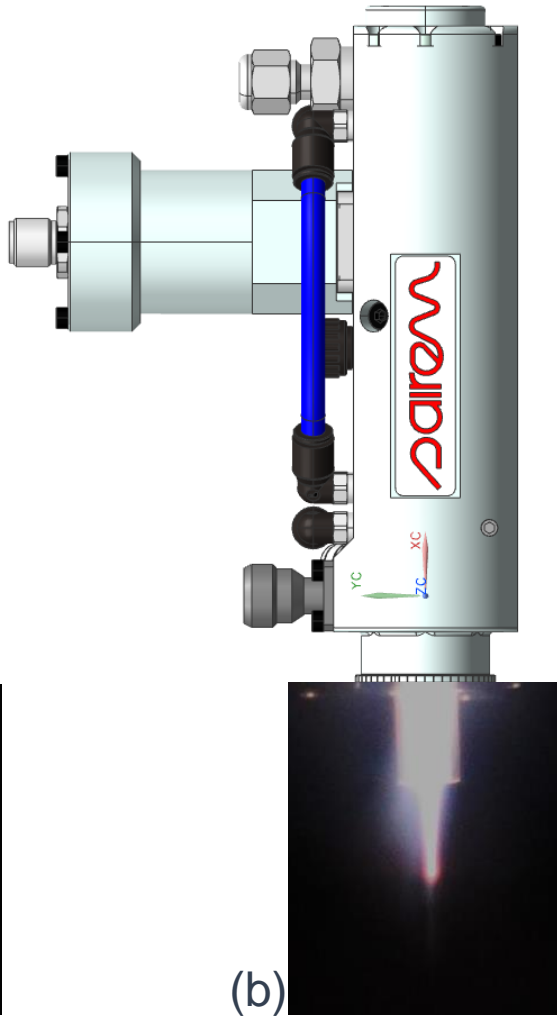
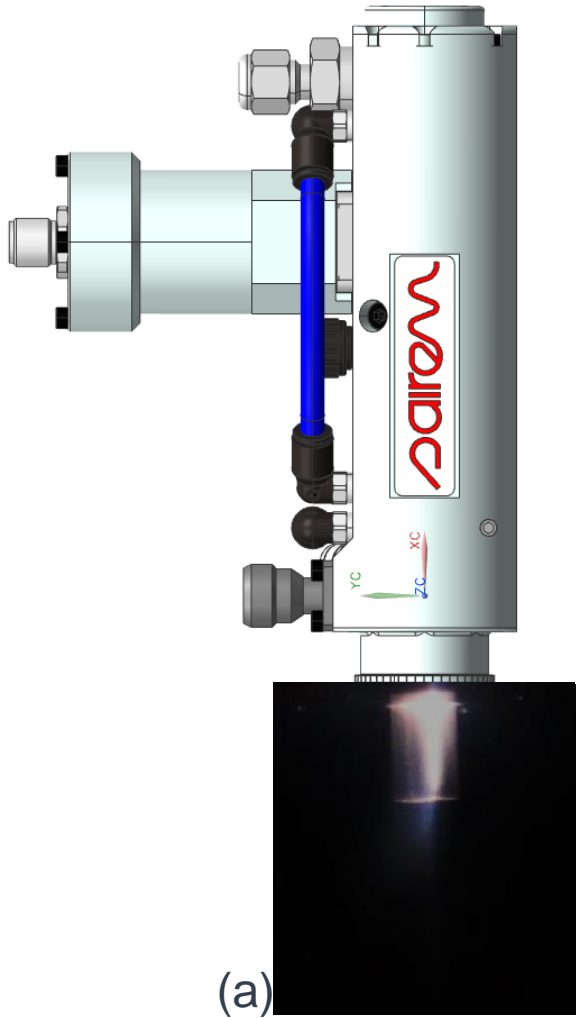


TE₁₁

$$f_{mnp} = \frac{c}{2\pi\sqrt{\mu_r\epsilon_r}} \cdot \sqrt{\left(\frac{X'_{mn}}{R}\right)^2 + \left(\frac{p\pi}{L}\right)^2}$$

TE f ≠ TM f

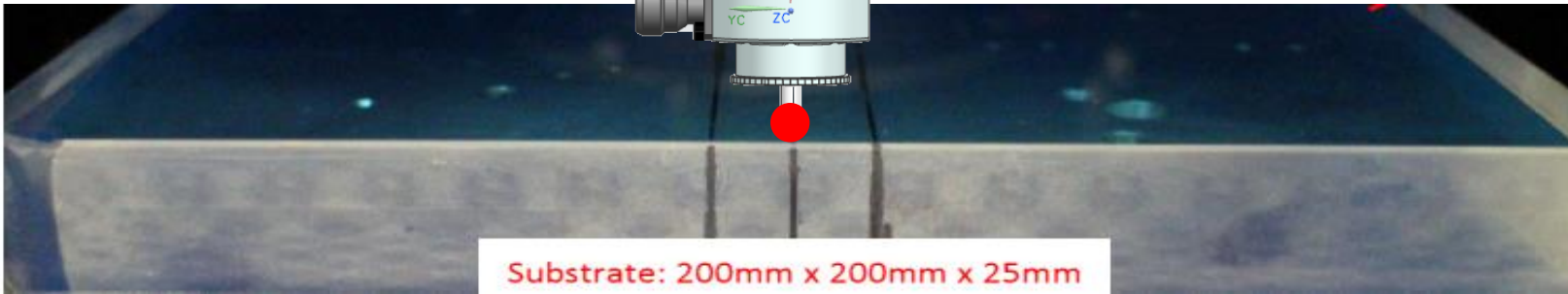
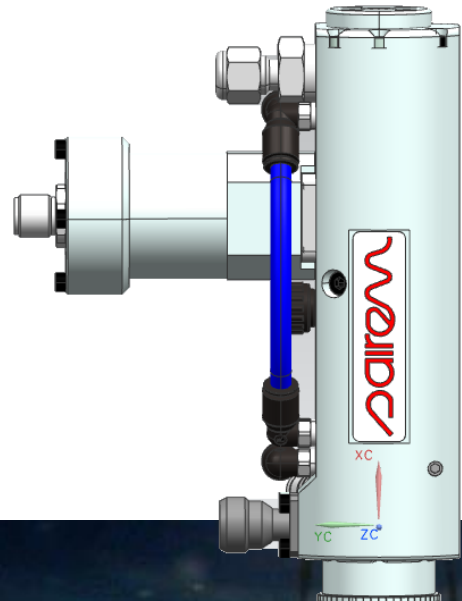
Plasma Processing



Plasma Jets:

- (a) 25W 5L/min Ar;
- (b) 100W 5L/min Ar;
- (c) 200W 5L/min Ar.

Plasma Processing Stationary Dwell – Material Removal

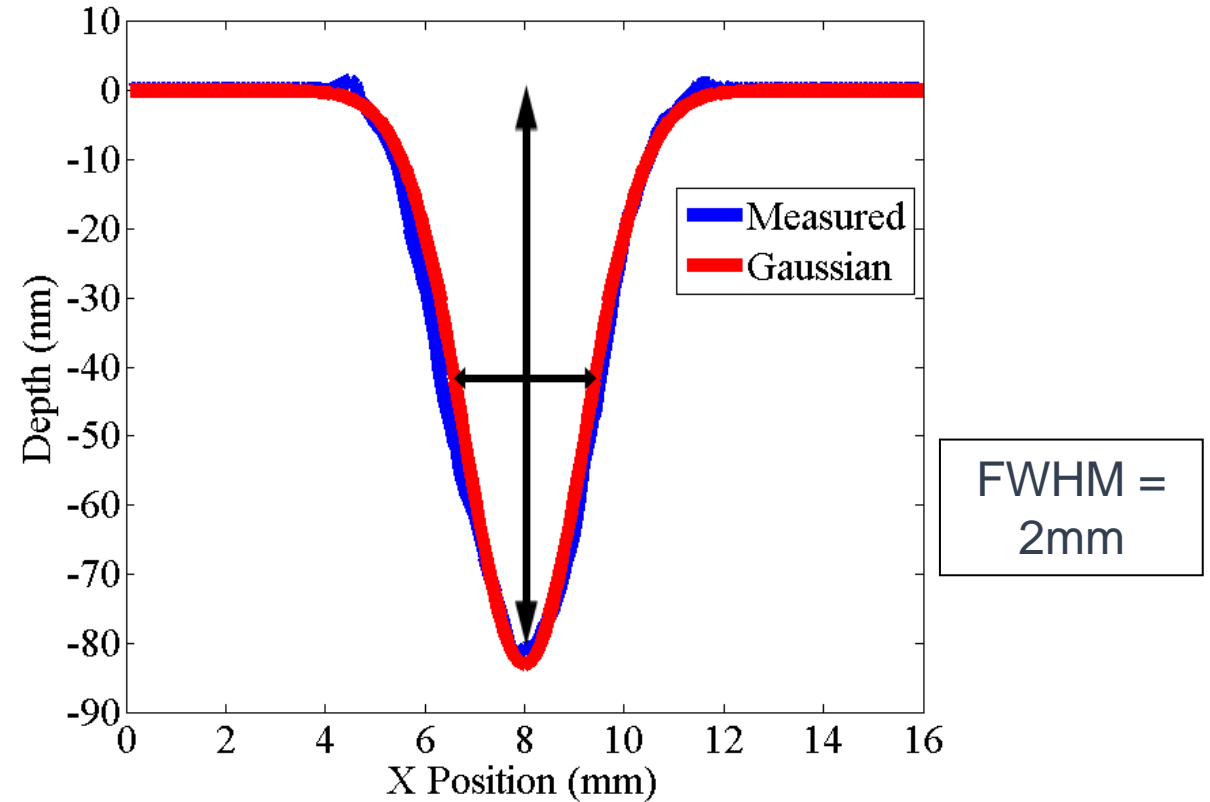
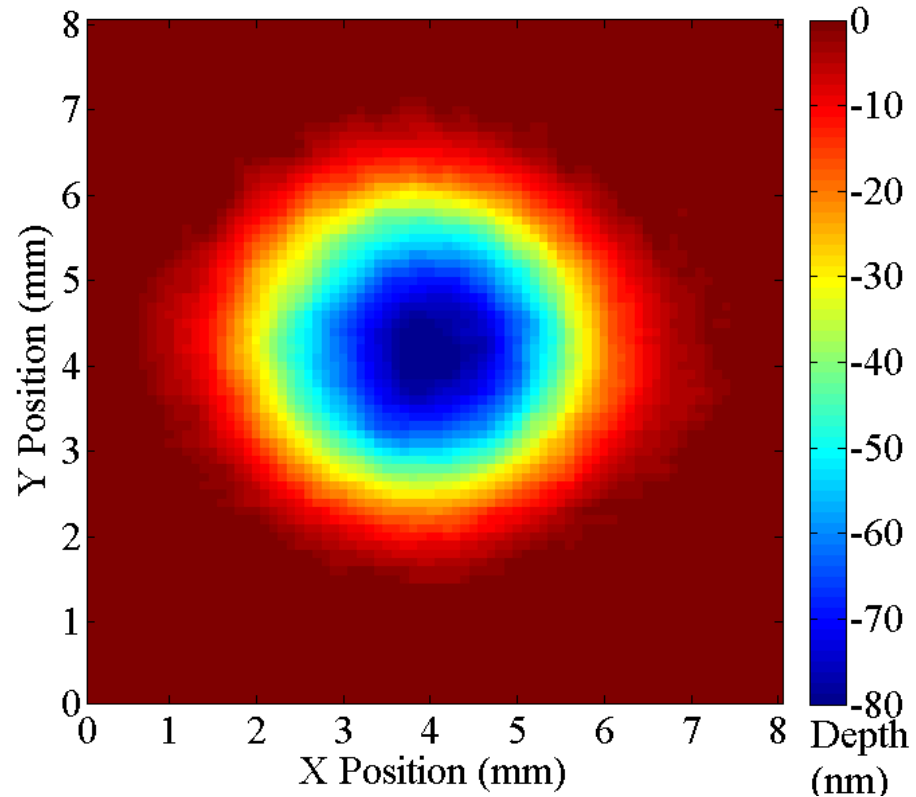


Substrate: 200mm x 200mm x 25mm

Plasma Processing Stationary Dwell – Material Removal

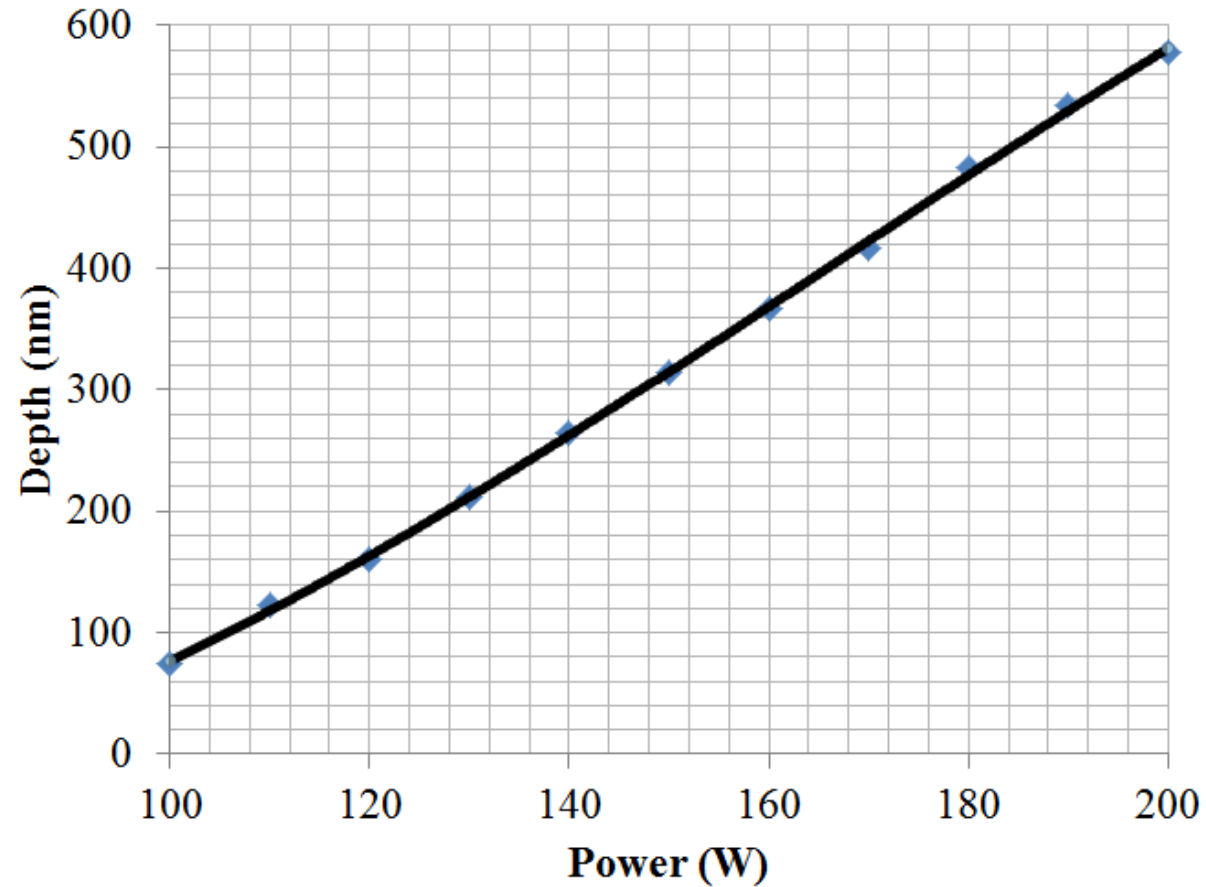
Power = 100W, Frequency = 2.45GHz, Main Gas Flow = Argon @ 5L/min,
Reactive Gas Flow = 10% CF4 in Argon @ 0.5L/min, Stand-Off Distance = 10mm, Dwell Time = 10s

Optical Substrate = ULE

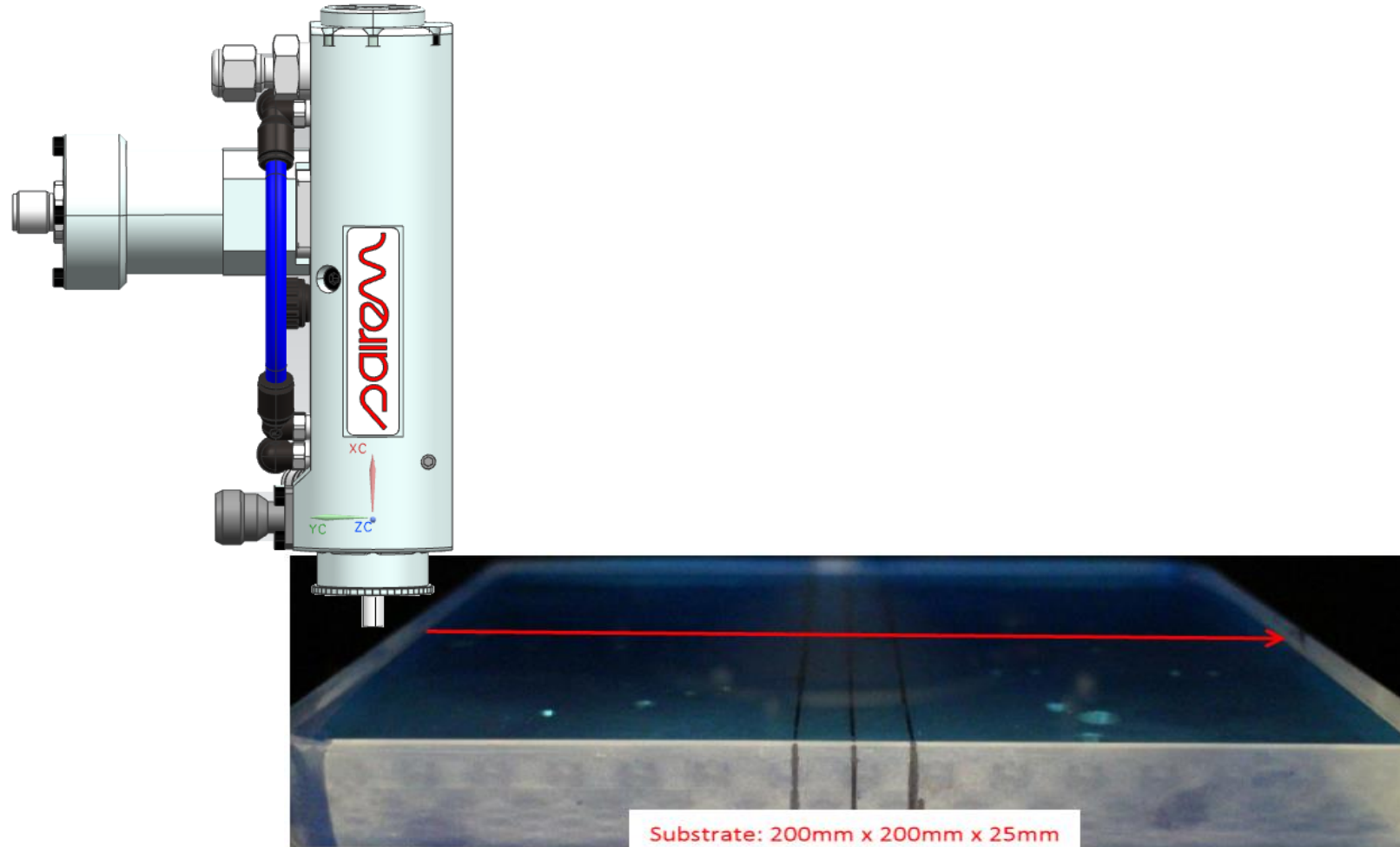


Plasma Processing Stationary Dwell – Material Removal

Power effect on maximum depth

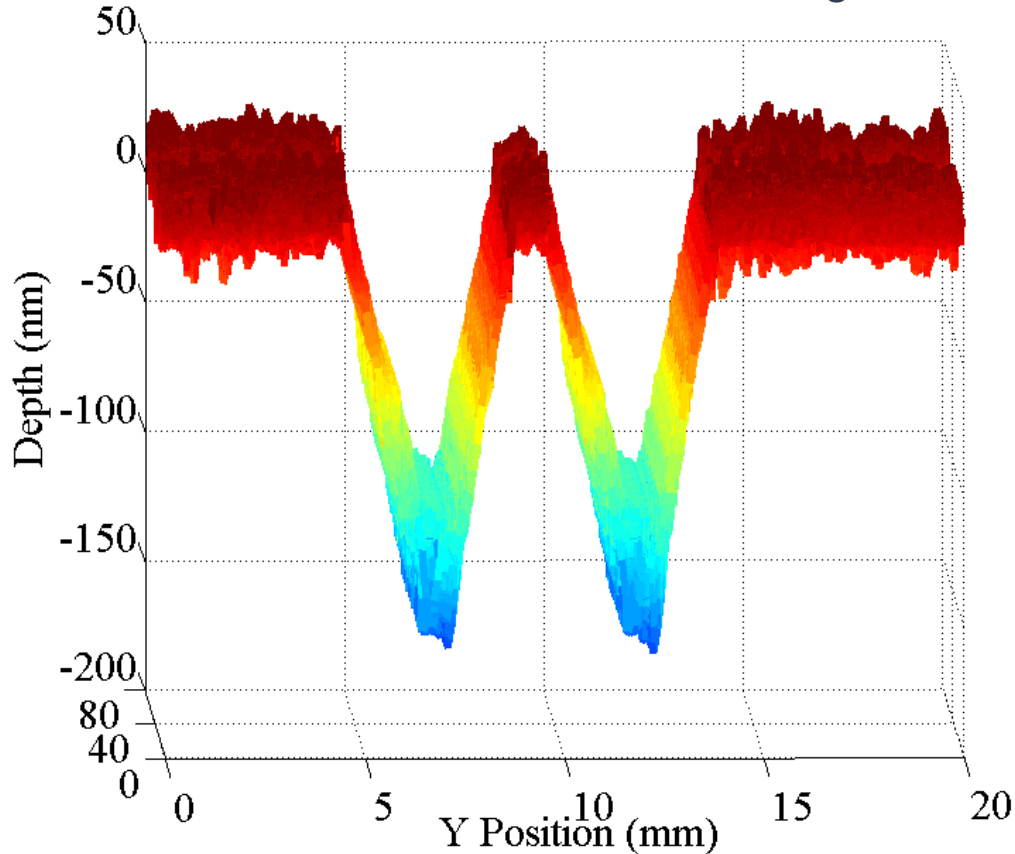


Plasma Processing Single Trench – Material Removal



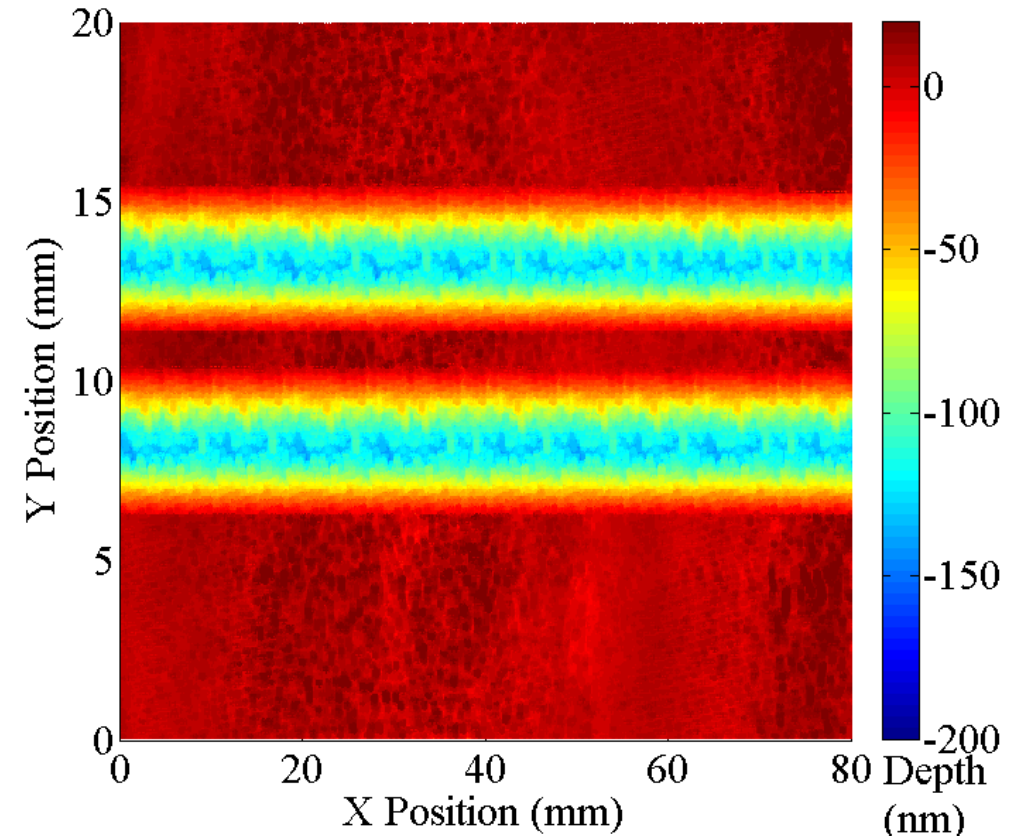
Plasma Processing Single Trench – Material Removal

Power = 150W, Frequency = 2.45GHz, Main Gas Flow = Argon @ 5L/min,
Reactive Gas Flow = 10% CF4 in Argon @ 0.5L/min, Stand-Off Distance = 10mm, Optical Substrate = ULE



FWHM =
2mm

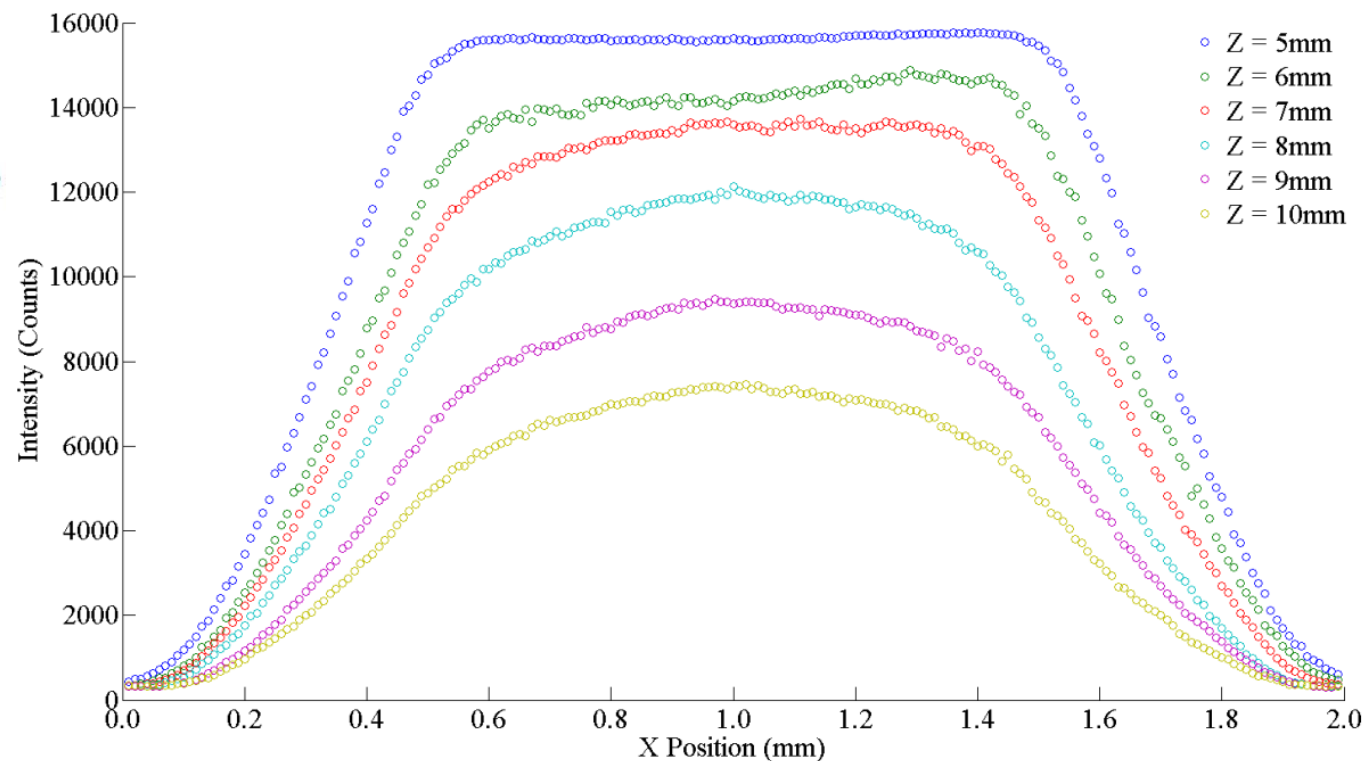
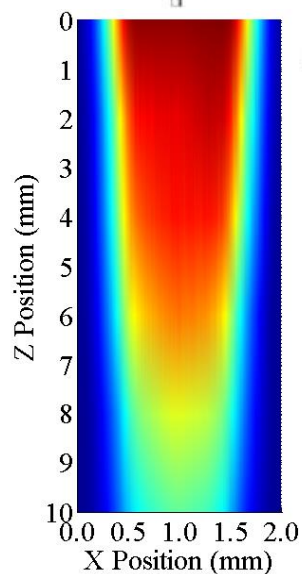
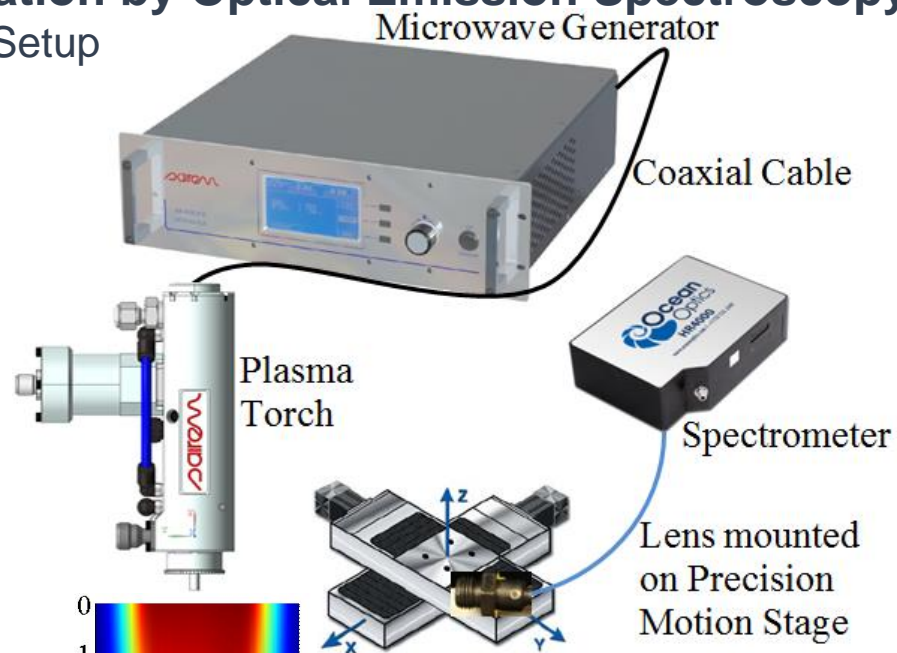
Torch
Speed =
10mm/min



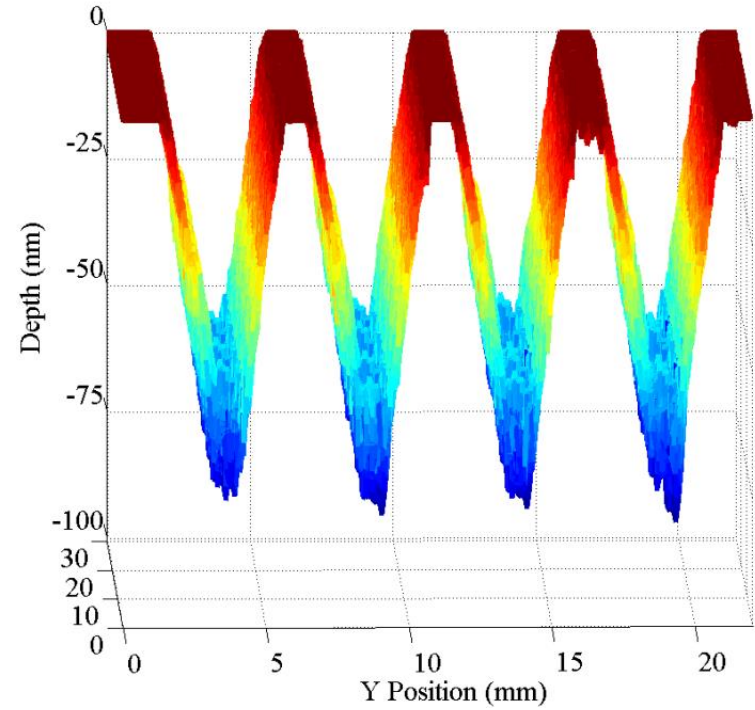
Surface Wave Launched Microwave Induced Plasma Torch

Characterisation by Optical Emission Spectroscopy

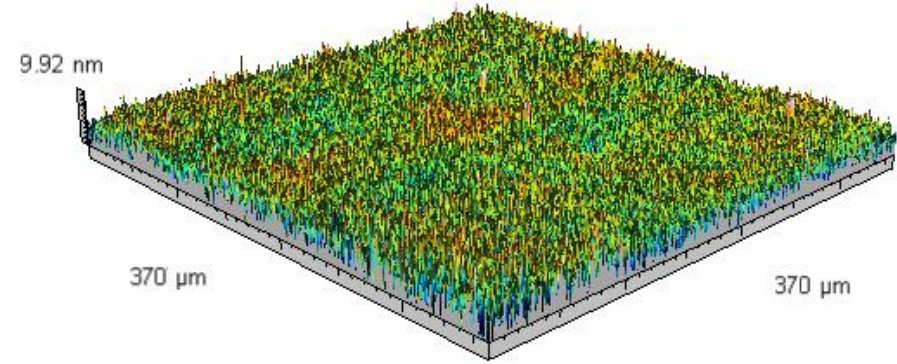
Experimental Setup



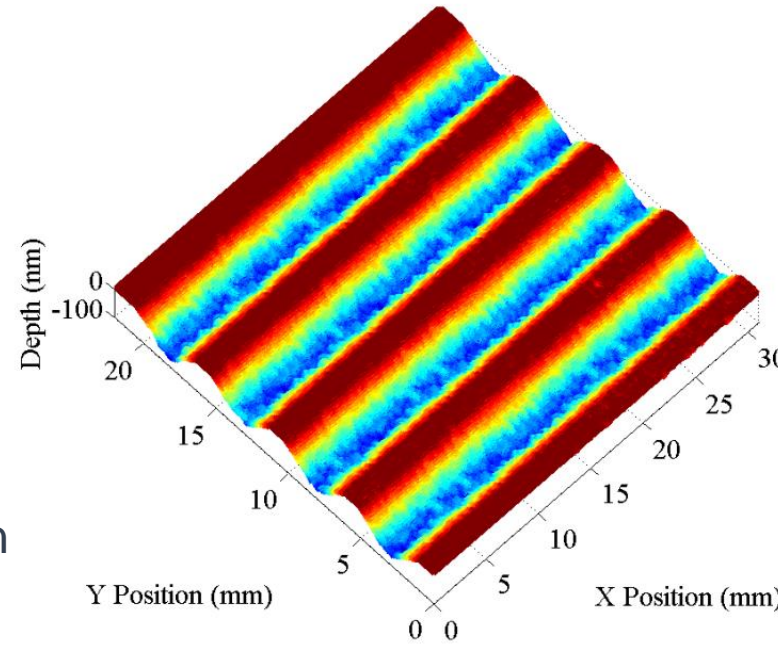
Plasma Processing Surface Figuring – Material Removal – Crystal Quartz



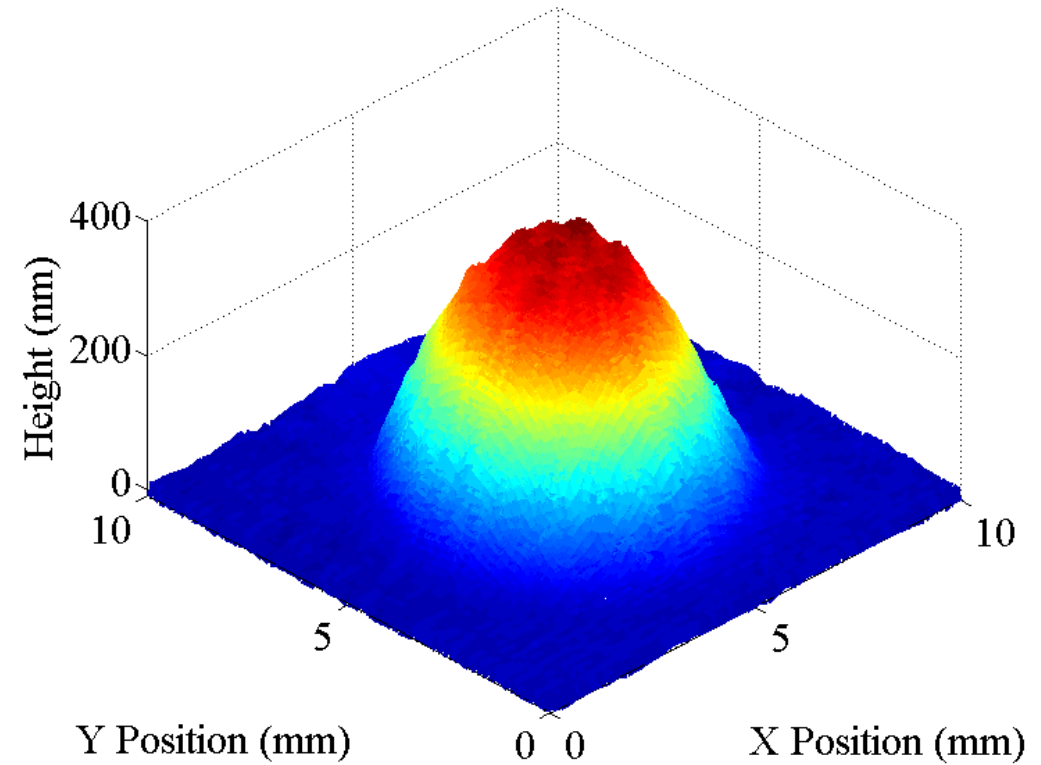
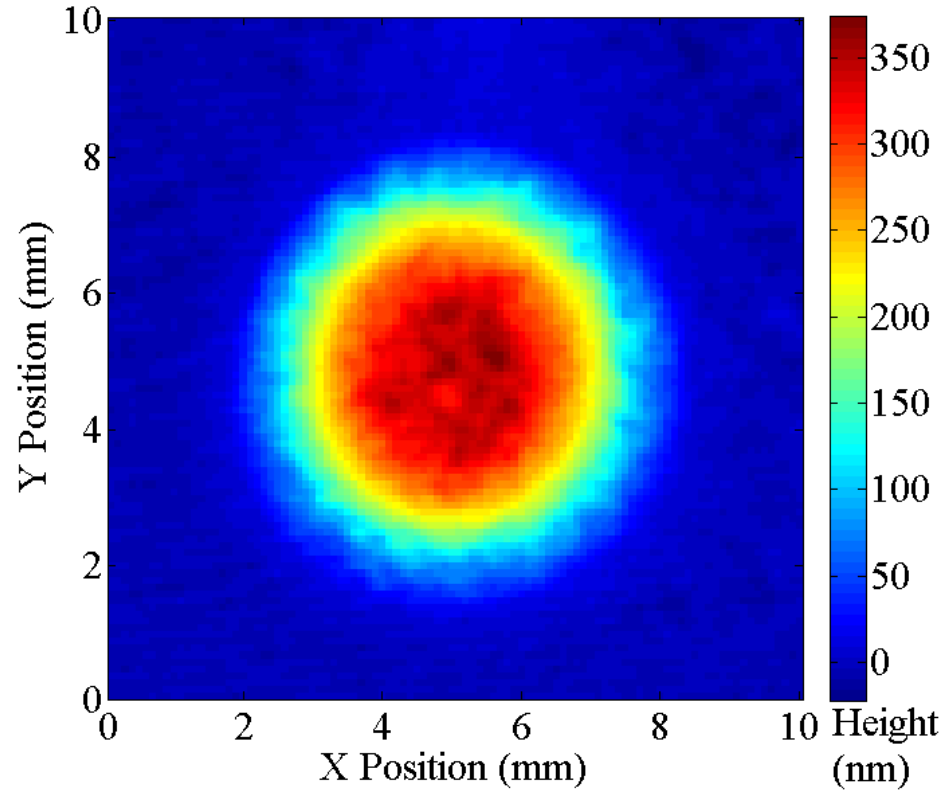
Form Correction
Capability



Surface Roughness



Plasma Processing Stationary Dwell – Material Deposition



Summary

Novel Microwave Spectrum & Optical Emission Spectroscopy techniques developed to characterise plasma torches.

New microwave plasma system has been commissioned and installed into the plasma figuring machine.

Stable material removal on the surface of optics has been demonstrated.

Full Design Of Experiments conducted to optimise the parameters.

Entire surface of Crystal Quartz substrates have been processed.

Deposition has also been demonstrated!

Acknowledgements

Cranfield University EPSRC Centre for Innovative Manufacturing in Ultra Precision {EP/I033491/1}: Plasma Figuring Laboratory

University Of Cambridge EPSRC Centre for Doctoral Training in Ultra Precision {EP/K503241/1}: Project Funding

Gooch & Housego: Project Funding

ADTEC: Technical Support & Pioneering Microwave Plasma System Loan

Defence Academy: Military Grade Microwave Characterisation



Adam Bennett

Doctoral Research Scientist

EPSRC Centre for Doctoral Training in Ultra Precision

<http://www.CDT-UP.Eng.Cam.ac.uk/People/Adam-Bennett>

EPSRC Centre for Innovative Manufacturing in Ultra Precision

<http://www.UltraPrecision.org>

<https://www.Linkedin.com/in/AdamDMBennett>

